

DESCRIPTION

PROJECTION OPTICAL SYSTEM, EXPOSURE APPARATUS, AND EXPOSURE METHOD

Technical Field

5 The present invention relates to a projection optical system, exposure apparatus, and exposure method and, more particularly, to a high-resolution projection optical system suitable for exposure apparatus used in production of semiconductor devices, liquid-crystal display devices, etc. by photolithography.

10 Background Art

 The photolithography for production of the semiconductor devices and others is implemented using a projection exposure apparatus for projecting a pattern image of a mask (or a reticle) through a projection optical system onto a wafer (or a glass plate or the like) coated with a photoresist or the like. resolving power (resolution) required for the projection optical system of the projection exposure apparatus is becoming increasingly higher and higher with increase in integration degree of the semiconductor devices and others.

 As a result, in order to satisfy the requirements for the resolving power of the projection optical system, it is necessary to shorten the wavelength λ of illumination light (exposure light) and to increase the image-side numerical aperture NA of the projection optical system. Specifically, the resolution of the projection optical system is expressed by $k\lambda/NA$ (where k is the process coefficient). The image-side numerical aperture NA is represented by $n\sin\theta$, where n is a refractive index of a medium (normally, gas such as air) between the projection

20

25

optical system and the photosensitive substrate (a wafer or the like) and θ a maximum angle of incidence to the photosensitive substrate.

In this case, if the maximum incidence angle θ is increased in order to increase the image-side numerical aperture, it will result in increasing the incidence angle to the photosensitive substrate and the emergence angle from the projection optical system, and therefore increasing reflection loss on optical surfaces. Thus it will fail to secure a large effective image-side numerical aperture. For this reason, as described later, there is the known technology of increasing the image-side numerical aperture by filling a medium like a liquid with a high refractive index in the optical path between the projection optical system and the photosensitive substrate.

On the other hand, as to the degree of difficulty of production of optical systems, the dioptric projection optical systems comprised of only refracting members have the difficulty degree lower than the catadioptric projection optical systems including a reflecting member, and thus the dioptric projection optical systems are more suitable for mass supply of exposure apparatus. In the dioptric projection optical systems, however, a lens unit with a positive refracting power and a lens unit with a negative refracting power need to be located with a space, in order to satisfy the Petzval's condition on the object side (mask side) with respect to the pupil thereof. For realizing the large image-side numerical aperture of not less than 1 as described above, the object-side numerical aperture also increases therewith.

In the dioptric projection optical systems, it will result in failing to well correct for off-axis aberrations such as coma and, in turn, failing

to secure a large still exposure region (effective exposure region: effective imaging area) and to avoid an increase in the size of lenses. Then, it is also conceivable to adopt a method of setting the projection magnification (image magnification) of the projection optical system smaller than normal, so as to keep the object-side numerical aperture at a low level, thereby well correcting for the off-axis aberrations and avoiding an increase in the size of lenses. However, if the projection magnification of the projection optical system is set smaller than normal, it will result in increasing the mask-side illumination area optically corresponding to a shot-area having a required size, and thus failing to cover this large illumination area by a currently predominating 6-inch reticle.

Nowadays, the exposure apparatus equipped with the projection optical system having the relatively large image-side numerical aperture adopts the step-and-scan system for implementing scanning exposure of a mask pattern in one shot-area on a wafer while moving the mask and wafer relative to the projection optical system. However, if a configuration wherein a medium is filled in the optical path between the projection optical system and the photosensitive substrate is adopted in order to achieve the large image-side numerical aperture, quick scanning exposure is impossible, for example, because of the intervention of the liquid-like medium, and it could cause a drop of throughput.

The present invention has been accomplished in view of the above problems and an object of the invention is to provide an exposure apparatus and exposure method capable of effecting high-resolution projection exposure with high throughput, while securing a large

effective image-side numerical aperture through the intervention of a high-refractive-index medium in the optical path between the projection optical system and the photosensitive substrate, using the dioptric projection optical system easy to produce and the mask of the ordinary size.

Disclosure of the Invention

In order to achieve the above object, an exposure method according to a first aspect of the present invention is an exposure method of effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate, the exposure method comprising:

a filling step of filling an optical path between the projection optical system and the photosensitive substrate with a medium having a refractive index larger than 1.1, where a refractive index of an atmosphere in an optical path of the projection optical system is 1; and

an exposure step of effecting a projection exposure in one shot-area on the photosensitive substrate,

wherein the shot-area includes a plurality of partial exposure regions, and

wherein the exposure step is to repeat an exposure in the partial exposure region more than once.

Another exposure method according to a second aspect of the present invention is an exposure method of effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate, the exposure method comprising:

a filling step of filling an optical path between the projection optical system and the photosensitive substrate with a medium having a refractive index larger than 1.1, where a refractive index of an atmosphere in an optical path of the projection optical system is 1;

5 a first exposure step of performing a projection exposure in a first still exposure region on the photosensitive substrate in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system;

10 a moving step of moving at least the photosensitive substrate relative to the projection optical system, in order to perform a projection exposure in a second still exposure region not adjoining the first still exposure region subjected to the projection exposure in the first exposure step, the moving step being executed directly after the first exposure step; and

15 a second exposure step of performing the projection exposure in the second still exposure region on the photosensitive substrate in the state in which the mask and the photosensitive substrate are kept still relative to the projection optical system, the second exposure step being executed directly after the moving step.

20 An exposure apparatus according to a third aspect of the present invention is an exposure apparatus for effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate,

25 wherein an optical path between the projection optical system and the photosensitive substrate is filled with a medium having a refractive index larger than 1.1 where a refractive index of an

atmosphere in an optical path of the projection optical system is 1,

wherein the projection optical system has a still exposure region substantially smaller than one shot-area to be formed on the photosensitive substrate, and

5 wherein the projection optical system repeats a projection exposure in a portion of the shot-area more than once in the projection exposure in the shot-area.

Another exposure apparatus according to a fourth aspect of the present invention is an exposure apparatus for effecting a projection
10 exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate, the exposure apparatus comprising:

 a substrate stage for holding the photosensitive substrate in a movable state;

15 means for filling an optical path between the projection optical system and the photosensitive substrate with a medium having a refractive index larger than 1.1, where a refractive index of an atmosphere in an optical path of the projection optical system is 1; and

 control means for controlling at least the substrate stage so as to
20 perform a projection exposure in a first still exposure region on the photosensitive substrate in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system, to, subsequent to the projection exposure in the first still exposure region, move at least the photosensitive substrate relative to
25 the projection optical system in order to perform a projection exposure in a second still exposure region not adjoining the first still exposure

region subjected to the projection exposure in the first exposure step, and to, subsequent to the relative movement of the photosensitive substrate, perform the projection exposure in the second still exposure region on the photosensitive substrate in the state in which the mask and the photosensitive substrate are kept still relative to the projection optical system.

A projection optical system according to a fifth aspect of the present invention is a projection optical system for forming a reduced image of a first surface on a second surface,

wherein an optical path between the projection optical system and the second surface is filled with a medium having a refractive index larger than 1.1 where a refractive index of an atmosphere in an optical path of the projection optical system is 1,

wherein every optical member having a power in the projection optical system is a transmitting optical member,

wherein a magnification of the projection optical system is not more than $1/8$, and

wherein the projection optical system is substantially telecentric on both the first surface side and the second surface side.

Another exposure method according to the sixth aspect of the present invention is an exposure method of effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate, the exposure method comprising:

a preparation step of preparing the projection optical system having a magnification of not more than $1/8$;

a filling step of filling an optical path between the projection optical system and the photosensitive substrate with a medium having a refractive index larger than 1.1, where a refractive index of an atmosphere in an optical path of the projection optical system is 1; and

5 an exposure step of effecting a projection exposure in one shot-area on the photosensitive substrate,

wherein the exposure step is to perform the projection exposure in one shot-area including a plurality of partial exposure regions, and

10 wherein the exposure step comprises a plurality of partial exposure steps each of which is to perform a projection exposure in the partial exposure region.

Brief Description of the Drawings

Fig. 1 is an illustration schematically showing a configuration of an exposure apparatus according to an embodiment of the present invention.

Fig. 2 is an illustration schematically showing a configuration between a boundary lens and a wafer in each example.

Fig. 3 is an illustration showing a lens configuration of a projection optical system according to the first example of the embodiment of the present invention.

Fig. 4 is an illustration showing the transverse aberration in the first example.

Fig. 5 is an illustration showing the relationship between a shot-area and partial exposure regions in the first example.

25 Fig. 6 is an illustration showing a lens configuration of a projection optical system according to the second example of the

embodiment of the present invention.

Fig. 7 is an illustration showing the transverse aberration in the second example.

5 Fig. 8 is an illustration showing the relationship between a shot-area and partial exposure regions in the second example.

Fig. 9 is an illustration showing a lens configuration of a projection optical system according to the third example of the embodiment of the present invention.

10 Fig. 10 is an illustration showing the transverse aberration in the third example.

Fig. 11 is an illustration showing the relationship between a shot-area and partial exposure regions in the third example.

15 Fig. 12 is an illustration showing a lens configuration of a projection optical system according to the fourth example of the embodiment of the present invention.

Fig. 13 is an illustration showing the transverse aberration in the fourth example.

20 Fig. 14 is an illustration showing a lens configuration of a projection optical system according to the fifth example of the embodiment of the present invention.

Fig. 15 is an illustration showing the transverse aberration in the fifth example.

25 Fig. 16 is an illustration showing the relationship between a shot-area and partial exposure regions in the fourth example and the fifth example.

Figs. 17A to 17D are illustrations showing an operation of

repeatedly performing partial exposure steps for a plurality of shot-areas on one wafer in the fourth example and the fifth example.

Fig. 18 is a flowchart of a method of producing semiconductor devices as microdevices.

5 Fig. 19 is a flowchart of a method of producing a liquid-crystal display device as a microdevice.

Best Mode for Carrying out the Invention

10 The present invention involves interposing the medium with the refractive index larger than 1.1 in the optical path between the projection optical system and the photosensitive substrate, thereby increasing the image-side numerical aperture NA of the projection optical system. In passing, "Resolution Enhancement of 157-nm Lithography by Liquid Immersion" reported in "Massachusetts Institute of Technology" in "SPIE2002 Microlithography" by Mr. M. Switkes and
15 Mr. M. Rothschild describes Fluorinert (Perfluoropolyethers: trade name of 3M, USA) and Deionized Water as candidates for media having the required transmittance for light of wavelength λ of not more than 200 nm.

20 In the present invention, as described above, the high-refractive-index medium, e.g., a liquid (or fluid) is interposed in the optical path between the projection optical system and the photosensitive substrate, whereby the high-resolution projection exposure can be performed while securing a large effective image-side numerical aperture.

25 A typical aspect of the present invention comprises performing a first still projection exposure in a partial exposure region having the size of about a half of one shot-area, for example, using the projection

optical system having the projection magnification of not more than $1/5$, and, after replacement of the mask, performing a second still projection exposure in the rest partial exposure region in the size of about half. In this configuration, the projection magnification of the projection optical system is set smaller than the normal projection magnification (i.e., $1/4$); therefore, the object-side numerical aperture does not substantially increase even if the image-side numerical aperture becomes larger than the ordinary values by virtue of the intervention of the high-refractive-index medium.

As a result, even with use of the dioptric projection optical system easy to manufacture, a satisfactorily large still exposure region can be secured by well correcting for the off-axis aberrations such as coma, and an increase in the size of lenses is also avoided. Since the mask is replaced with another between two still projection exposures in the partial exposure regions having the size of about a half of one shot-area, the 6-inch reticle, which is presently mainstream as a mask, can be used. Furthermore, the present invention employs the configuration wherein the medium is filled in the optical path between the projection optical system and the photosensitive substrate in order to achieve the large image-side numerical aperture, and the still projection exposure is performed so as not to cause a drop of throughput due to the intervention of the medium, different from the case of scanning exposure.

In one aspect of the present invention, as described above, the high-resolution projection exposure can be performed with high throughput while securing the large effective image-side numerical

aperture through the intervention of the high-refractive-index medium in the optical path between the projection optical system and the photosensitive substrate, using the dioptric projection optical system easy to manufacture and the mask of the ordinary size.

5 Incidentally, the current shot-area is a rectangular region of 33 mm $\times$ 26 mm or 33 mm $\times$ 22 mm. This is a shot-area that can be obtained by one-shot projection exposure using the reticle of 6-inch size and the projection optical system having the projection magnification of 1/4. In the case where this shot-area is equally divided into two partial
10 exposure regions and where two still projection exposures are carried out, the size of each partial exposure region is 26 mm $\times$ 16.5 mm or 22 mm $\times$ 16.5 mm. When the size of each partial exposure region is 26 mm $\times$ 16.5 mm, it is feasible to perform the one-shot projection exposures using the reticle of 6-inch size and the projection optical
15 system having the projection magnification of 1/5.

On the other hand, where the size of each partial exposure region is 22 mm $\times$ 16.5 mm, it is feasible to perform the one-shot projection exposures using the reticle of the 6-inch size and the projection optical system having the projection magnification of 1/6.
20 In passing, where the aforementioned shot-area is equally divided into four partial exposure regions and where four still projection exposures are carried out, the size of each partial exposure region is, for example, 13 mm $\times$ 16.5 mm. In this case, since the still exposure regions can be relatively small, it is feasible to perform the one-shot projection
25 exposures using the projection optical system having the ordinary projection magnification of 1/4 and the reticle of 6-inch size.

If the large image-side numerical aperture of not less than 1 is intended to be realized in the projection optical system with the projection magnification of $1/4$ which is presently predominating, the object-side numerical aperture will also increase to some extent therewith. As a result, in the case of the dioptric projection optical system, the increase of the object-side numerical aperture could lead to failure in well correcting for the off-axis aberrations such as coma and, in turn, failure in securing the large still exposure region (effective exposure region: effective imaging area), and it also becomes difficult to avoid an increase in the size of lenses.

Then, it is also conceivable to adopt a method of setting the projection magnification (image magnification) of the projection optical system smaller than normal so as to keep the object-side numerical aperture at a low level, thereby well correcting for the off-axis aberrations and also avoiding the increase in the size of lenses. However, where the projection magnification of the projection optical system is set smaller than normal, it will result in an increase in the mask-side illumination area optically corresponding to the shot-area having the required size and this large illumination area cannot be covered by the presently predominating 6-inch reticle.

In fact, IC devices and the like are constructed of a plurality of layers, and it is not the case that all the layers are exposed with use of the same exposure apparatus. Therefore, it is important to use the shot-areas common to the current exposure apparatus. Since the required size of the shot-areas is determined on the image side of the projection optical system, if the projection magnification of the projection optical

system is set to a value smaller than current $1/4$, the required mask area will become larger than the current mask area. In other words, if the projection magnification of the projection optical system is made simply smaller than current $1/4$, the presently predominating 6-inch reticle will fail to cover the required shot-area.

However, since the magnification of the projection optical system according to another aspect of the present invention is not more than $1/8$, the object-side numerical aperture can be kept at a small level even if the image-side numerical aperture is kept large. As a result, even the dioptric projection optical system is able to well correct for the off-axis aberrations such as coma and, in turn, to secure the relatively large effective imaging area, without increase in the size of lenses.

Namely, according to another aspect of the present invention, it is feasible to realize the dioptric projection optical system capable of securing the relatively large effective imaging area while securing the large effective image-side numerical aperture through the intervention of the high-refractive-index medium in the optical path to the image surface. The exposure apparatus and exposure method using the projection optical system according to another aspect of the present invention involve repeating a still projection exposure in each partial exposure region four times in the projection exposure in one shot-area including four partial exposure regions, for example, using four separate 6-inch reticles. In this case, it is feasible to keep the maximum image height required for the projection optical system, at a low level and, in turn, to achieve miniaturization of the projection optical system.

The configuration of filling the medium in the optical path to the

photosensitive substrate is adopted in order to achieve the large image-side numerical aperture, but the still projection exposures are carried out through the dioptric projection optical system, which does not cause a drop of throughput due to the intervention of the medium, different from the case of scanning exposure. As described above, the exposure apparatus and exposure method of the present invention use the dioptric projection optical system easy to manufacture and the mask of the normal size and are able to perform the high-resolution projection exposure with high throughput, while securing the large effective image-side numerical aperture through the intervention of the high-refractive-index medium in the optical path between the projection optical system and the photosensitive substrate.

The projection optical system according to another aspect of the present invention preferably satisfies Condition (1) below, where L2 is the distance from the image-side pupil position to the image surface and LA the distance from the object surface (first surface) to the image surface, i.e., object-image distance.

$$0.18 < L2/LA < 0.245 \quad (1)$$

The range below the lower limit of Condition (1) is undesirable because it becomes difficult to correct for coma, astigmatism, and the like and to obtain an effective imaging area. On the other hand, the range above the upper limit of Condition (1) is undesirable because the size of the optical system becomes larger. Namely, when the projection optical system satisfies Condition (1), the reduction projection optical system can be constructed in the feasible size while securing the necessary and sufficient effective imaging area. For better

demonstrating the effect of the present invention, the lower limit of Condition (1) is preferably set to 0.2 and the upper limit thereof to 0.24.

The projection optical system according to another aspect of the present invention preferably has at least one variable aperture stop disposed at or near the image-side pupil position. This configuration permits us to select an optimal numerical aperture for imaging with respect to masks having a variety of patterns. Furthermore, by disposing two variable aperture stops with a space in the optical-axis direction, it becomes feasible to uniformize the pupil shape throughout the entire effective imaging area at a variety of numerical apertures. For the detailed operational effect of the two variable aperture stops disposed with a space in the optical-axis direction, reference should be made to Japanese Patent Application Laid-Open No. 2002-118053 and WO02/31870 corresponding thereto.

The projection optical system according to another aspect of the present invention preferably has a first lens unit with a positive refracting power, a second lens unit with a negative refracting power, a third lens unit with a positive refracting power, a fourth lens unit with a negative refracting power, a fifth lens unit with a positive refracting power, an aperture stop, and a sixth lens unit with a positive refracting power, and satisfies Condition (2) below.

$$0.04 < P2/PX < 0.2 \quad (2)$$

In Condition (2), where a size of an area occupied on each optical surface by a beam from a point on the optical axis of the object surface is defined as a partial diameter, PX is a maximum partial diameter in the projection optical system and P2 a minimum partial

diameter in the second lens unit. For the general definition of the partial diameter (partial size: partial beam size[diameter]), reference should be made to Paragraph [0032] and Fig. 3 of Japanese Patent Application Laid-Open No. 2002-151397, and to Paragraphs [0084]-
5 [0089] and Fig. 14 of Japanese Patent Application Laid-Open No. 2002-258131 (and Paragraphs [0114]-[0119] and Fig. 14 of European Patent Publication EP1359608 corresponding thereto).

When Condition (2) is met, it is feasible to efficiently satisfy the Petzval's condition and to realize good imaging performance with
10 excellent flatness. Namely, the range below the lower limit of Condition (2) is undesirable because a sufficient working distance cannot be secured on the mask side and mechanical interference of a mask stage becomes likely to occur in application to the exposure apparatus. On the other hand, the range over the upper limit of
15 Condition (2) is undesirable because it becomes difficult to avoid an increase of the lens diameter or degradation of aberration performance (the Petzval's condition). For better demonstrating the effect of the present invention, the lower limit of Condition (2) is preferably set to 0.06 and the upper limit thereof to 0.15.

20 The projection optical system according to another aspect of the present invention preferably satisfies Condition (3) below, in addition to above-described Condition (2). In Condition (3), D4 is a minimum clear aperture radius of a lens in the fourth lens unit and D0 a clear aperture radius of the object surface (a mask in application to the
25 exposure apparatus).

$$0.4 < D4/D0 < 0.9 \quad (3)$$

The range below the lower limit of Condition (3) is undesirable because it becomes infeasible to achieve a sufficiently large image-side numerical aperture. On the other hand, the range above the upper limit of Condition (3) is undesirable because it becomes difficult to avoid an increase in the lens diameter or degradation of aberration performance (the Petzval's condition). For better demonstrating the effect of the present invention, the lower limit of Condition (3) is preferably set to 0.5 and the upper limit to 0.87.

Alternatively, the projection optical system according to another aspect of the present invention preferably has a first lens unit with a negative refracting power, a second lens unit with a positive refracting power, a third lens unit with a negative refracting power, a fourth lens unit with a positive refracting power, an aperture stop, and a fifth lens unit with a positive refracting power, and satisfies Condition (4) below. In Condition (4), PX is the maximum partial diameter in the projection optical system as described above, and P3 a minimum partial diameter in the third lens unit.

$$0.07 < P3/PX < 0.23 \quad (4)$$

When Condition (4) is met, it is feasible to efficiently satisfy the Petzval's condition and to realize good imaging performance with excellent flatness. Namely, the range below the lower limit of Condition (4) is undesirable because a sufficient working distance cannot be secured on the mask side and mechanical interference of the mask stage becomes likely to occur in application to the exposure apparatus. On the other hand, the range above the upper limit of Condition (4) is undesirable because it becomes difficult to avoid an

increase in the lens size or degradation of aberration performance (the Petzval's condition). For better demonstrating the effect of the present invention, the lower limit of Condition (4) is preferably set to 0.1 and the upper limit to 0.21.

5 The projection optical system according to another aspect of the present invention preferably satisfies Condition (5) below, in addition to above-described Condition (4). In Condition (5), D3 is a minimum clear aperture radius of a lens in the third lens unit, and D0 a clear aperture radius of the object surface (the mask in application to the exposure apparatus).

$$0.35 < D3/D0 < 0.85 \quad (5)$$

10 The range below the lower limit of Condition (5) is undesirable because it becomes infeasible to realize a sufficiently large image-side numerical aperture. On the other hand, the range above the upper limit of Condition (5) is undesirable because it becomes difficult to avoid an increase in the lens diameter or degradation of aberration performance (the Petzval's condition). For better demonstrating the effect of the present invention, the lower limit of Condition (5) is preferably set to 0.4 and the upper limit thereof to 0.8.

15 An embodiment of the present invention will be described below on the basis of the accompanying drawings.

20 Fig. 1 is an illustration schematically showing a configuration of an exposure apparatus according to an embodiment of the present invention, wherein the Z-axis is set in parallel with the optical axis AX of a projection optical system PL, the Y-axis in parallel with the plane of Fig. 1 within the plane normal to the optical axis AX, and the X-axis

normal to the plane of Fig. 1. The exposure apparatus depicted is provided with an ArF excimer laser source as a light source 100 for supplying illumination light in an ultraviolet region.

5 Light emitted from the light source 100 travels through an illumination optical system IL to illuminate a reticle R with a predetermined pattern formed thereon, in a superimposed manner. The optical path between the light source 100 and illumination optical system IL is hermetically sealed in a casing (not shown), and the space from the light source 100 to the optical member closest to the reticle in
10 the illumination optical system IL is replaced with an inert gas such as helium gas or nitrogen being gas with small absorptance for the exposure light, or maintained in a nearly vacuum state.

The reticle R is kept in parallel with the XY plane on a reticle stage RS, through a reticle holder RH. A pattern to be transcribed is
15 formed on the reticle R, and a rectangular pattern area is illuminated. The reticle stage RS is two-dimensionally movable along the reticle surface (i.e., the XY plane) by action of a driving system not illustrated, and is configured so that coordinates of the position thereof are measured by an interferometer RIF using a reticle moving mirror RM
20 and so that the position thereof is controlled based thereon.

Light from the pattern formed on the reticle R is guided through the projection optical system PL to form a reticle pattern image on a wafer W being a photosensitive substrate. The wafer W is kept in parallel with the XY plane on a wafer stage WS, through a wafer holder
25 table WT. Then the pattern image is formed in a still exposure region of rectangular shape on the wafer W so as to optically correspond to the

rectangular illumination area on the reticle R. The wafer stage WS is two-dimensionally movable along the wafer surface (i.e., the XY plane) by action of a driving system not shown, and is configured so that coordinates of the position thereof are measured by an interferometer WIF using a wafer moving mirror WM and so that the position thereof is controlled based thereon.

In the exposure apparatus of the present embodiment, the interior of the projection optical system PL is arranged to be kept hermetically sealed between an optical member located nearest to the reticle (lens L1 or plane-parallel plate P1 in each example) and a boundary lens Lb located nearest to the wafer among optical members constituting the projection optical system PL, and the gas inside the projection optical system PL is replaced with an inert gas such as helium gas or nitrogen, or kept in a nearly vacuum state. Furthermore, the reticle R and reticle stage RS are arranged on the narrow optical path between the illumination optical system IL and the projection optical system PL, and an interior of a casing (not shown) hermetically enclosing the reticle R and reticle stage RS is filled with an inert gas such as nitrogen or helium gas, or kept in a nearly vacuum state.

Fig. 2 is an illustration schematically showing the configuration between the boundary lens and the wafer in each example. Referring to Fig. 2, in each example the boundary lens Lb located nearest to the wafer in the projection optical system PL has a convex surface kept toward the reticle. In other words, the reticle-side surface Sb of the boundary lens Lb has a positive refracting power. The optical path between boundary lens Lb and wafer W is filled with a medium Lm

having a refractive index larger than 1.1. In the first to third examples, deionized water is used as the medium Lm. In the fourth and fifth examples, pure water is used as the medium Lm.

5 The interior of the optical path between boundary lens Lb in the projection optical system PL and wafer W can be continuously kept filled with the liquid medium Lm, for example, by the technology disclosed in PCT International Publication WO99/49504, the technology disclosed in Japanese Patent Application Laid-Open No. 10-303114 and U.S. Pat. No. 5,825,043, and so on. In the technology disclosed in
10 PCT International Publication WO99/49504, a liquid (medium Lm) adjusted at a predetermined temperature is supplied from a liquid supply device through a supply tube and a discharge nozzle so as to fill the optical path between boundary lens Lb and wafer W, and the liquid is collected from on the wafer W through a collection tube and an inflow
15 nozzle by the liquid supply device.

On the other hand, in the technology disclosed in Japanese Patent Application Laid-Open No. 10-303114 and U.S. Pat. No. 5,825,043, the wafer holder table WT is constructed in such a receptacle shape as to be able to accommodate the liquid (medium Lm), and the
20 wafer W is positioned and held by vacuum suction at the center of the inner bottom part (in the liquid). The distal part of the lens barrel of the projection optical system PL is arranged to reach the inside of the liquid and, in turn, the wafer-side optical surface of the boundary lens Lb is arranged to reach the inside of the liquid.

25 As described above, an atmosphere with little absorption of the exposure light is created throughout the entire optical path from light

source 100 to wafer W. Accordingly, the driving systems, the interferometers (RIF, WIF), and others are used to perform the one-shot exposure while two-dimensionally driving and controlling the wafer W in the plane (XY plane) perpendicular to the optical axis AX of the projection optical system PL, whereby the pattern of reticle R is sequentially projected into shot-areas of wafer W by the so-called step-and-repeat method.

In each example, the lens components constituting the projection optical system PL are made of silica (SiO_2) or fluorite (CaF_2). The emission center wavelength of the ArF excimer laser light being the exposure light is 193.306 nm, the refractive index of silica for this center wavelength is 1.5603261, and the refractive index of fluorite is 1.5014548. Furthermore, in the first to third examples, deionized water having the refractive index of 1.47 for the exposure light is used as the medium Lm interposed between the boundary lens Lb and the wafer W. In each of the examples, the projection optical system PL is arranged to be substantially telecentric on both the object side and the image side.

In each example, an aspherical surface is expressed by mathematical expression (a) below, where y is a height in a direction normal to the optical axis, z a distance (sag) along the optical axis from a tangent plane at an apex of the aspherical surface to a position at the height y on the aspherical surface, r a radius of curvature at the apex, κ a conical coefficient, and C_n aspherical coefficients of order n. In each example, a lens surface formed in aspherical shape is accompanied by mark * on the right side to a surface number.

$$z = (y^2/r)/[1 + \{1 - (1 + \kappa) \cdot y^2/r^2\}^{1/2}] + C_4 \cdot y^4 + C_6 \cdot y^6 + C_8 \cdot y^8 + C_{10} \cdot y^{10} + C_{12} \cdot y^{12} + C_{14} \cdot y^{14} \quad (a)$$

[First Example]

Fig. 3 is an illustration showing a lens configuration of a projection optical system according to the first example of the present embodiment. With reference to Fig. 3, the projection optical system PL of the first example is composed of the following components arranged in order from the reticle side: a biconcave lens L1 whose concave surface of aspherical shape is kept toward the wafer; a negative meniscus lens L2 whose concave surface is kept toward the reticle; a positive meniscus lens L3 whose concave surface of aspherical shape is kept toward the reticle; a biconvex lens L4; a biconvex lens L5 whose convex surface of aspherical shape is kept toward the reticle; a positive meniscus lens L6 whose convex surface of aspherical shape is kept toward the reticle; a positive meniscus lens L7 whose concave surface of aspherical shape is kept toward the wafer; a negative meniscus lens L8 whose convex surface is kept toward the reticle; a biconcave lens L9 whose concave surface of aspherical shape is kept toward the reticle; a negative meniscus lens L10 whose concave surface of aspherical shape is kept toward the wafer; a biconcave lens L11 whose concave surface of aspherical shape is kept toward the wafer; a positive meniscus lens L12 whose concave surface of aspherical shape is kept toward the wafer; a biconvex lens L13; a positive meniscus lens L14 whose concave surface is kept toward the reticle; a positive meniscus lens L15 whose concave surface is kept toward the reticle; a negative meniscus lens L16 whose concave surface of aspherical shape is kept toward the

wafer; an aperture stop AS; a positive meniscus lens L17 whose concave surface is kept toward the reticle; a positive meniscus lens L18 whose concave surface is kept toward the reticle; a positive meniscus lens L19 whose convex surface is kept toward the reticle; a positive meniscus lens L20 whose convex surface is kept toward the reticle; a positive meniscus lens L21 whose concave surface of aspherical shape is kept toward the wafer; a positive meniscus lens L22 whose convex surface is kept toward the reticle; and a planoconvex lens L23 (boundary lens Lb) whose plane is kept toward the wafer.

In the first example, the optical path between the planoconvex lens L23 as the boundary lens Lb and the wafer W is filled with the medium Lm consisting of deionized water. The lenses L22 and L23 (Lb) are made of fluorite and the other lens components are made of silica.

Table (1) below presents values of specifications of the projection optical system PL in the first example. In Table (1), λ indicates the center wavelength of the exposure light, β the projection magnification (the imaging magnification of the entire system), and NA the image-side (wafer-side) numerical aperture. Each surface number represents an order of a surface from the reticle side, r a radius of curvature of each surface (in the case of an aspherical surface, a radius of curvature at the apex: mm), d an axial spacing or surface separation of each surface (mm), and n a refractive index for the center wavelength. The notations in Table (1) also apply to Tables (2) and (3) hereinafter.

TABLE 1

(Principal Specifications)

$$\lambda = 193.306 \text{ nm}$$

$$\beta = 1/5$$

$$NA = 1.04$$

5

(Specifications of Optical Members)

Surface No.	r	d	n	Optical Member
	(reticle surface)	35.85155		
1	-2116.15637	29.98465	1.5603261	(L 1)
10	2*	228.85023	79.18317	
3	-133.07210	20.30251	1.5603261	(L 2)
4	-306.24503	6.03952		
5*	-266.95498	49.96183	1.5603261	(L 3)
6	-187.00872	1.00000		
15	7	14334.34417	54.42808	1.5603261 (L 4)
8	-341.42581	1.00000		
9*	345.43150	57.60721	1.5603261	(L 5)
10	-31743139.73000	1.00000		
11*	211.82132	49.45639	1.5603261	(L 6)
20	12	455.88811	1.00000	
13	180.28560	39.08205	1.5603261	(L 7)
14*	221.90022	8.59172		
15	235.16731	43.22341	1.5603261	(L 8)
16	116.00174	67.18556		
25	17*	-195.60629	14.00000	1.5603261 (L 9)
18	130.52857	23.53252		

	19	2316.66653	14.00000	1.5603261	(L 1 0)
	20*	141.36693	28.05905		
	21	-832.06692	24.80161	1.5603261	(L 1 1)
	22*	781.19507	4.33285		
5	23	949.75316	14.83956	1.5603261	(L 1 2)
	24*	1429.30650	10.70117		
	25	7753.09495	42.50839	1.5603261	(L 1 3)
	26	-297.15092	1.58607		
	27	-576.53063	43.01673	1.5603261	(L 1 4)
10	28	-227.50556	1.00000		
	29	-8764.75335	30.82364	1.5603261	(L 1 5)
	30	-595.27589	1.00000		
	31	379.04693	30.00000	1.5603261	(L 1 6)
	32*	349.61368	44.68287		
15	33	∞	48.22674		(A S)
	34	-448.39487	45.40892	1.5603261	(L 1 7)
	35	-255.95110	1.00000		
	36	-2463.02432	37.63340	1.5603261	(L 1 8)
	37	-457.33179	1.00000		
20	38	219.60702	49.49656	1.5603261	(L 1 9)
	39	458.07732	1.00000		
	40	172.37588	49.09143	1.5603261	(L 2 0)
	41	318.22764	1.08037		
	42	154.21994	31.79043	1.5603261	(L 2 1)
25	43*	209.87548	1.17547		
	44	140.16986	44.87373	1.5014548	(L 2 2)

45	231.31932	5.59159		
46	256.60953	49.92220	1.5014548	(L 2 3 : L b)
47	∞	8.92710	1.47	(L m)
(wafer surface)				

5

(Aspherical Data)

2nd surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= -1.15575 \times 10^{-7} & C_6 &= 3.70303 \times 10^{-12} \\
 C_8 &= -1.15277 \times 10^{-16} & C_{10} &= 5.41093 \times 10^{-21} \\
 C_{12} &= -1.40182 \times 10^{-25} & C_{14} &= 1.39491 \times 10^{-29}
 \end{aligned}$$

10

5th surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= 1.03612 \times 10^{-8} & C_6 &= -2.91646 \times 10^{-13} \\
 C_8 &= 2.00780 \times 10^{-17} & C_{10} &= -6.27346 \times 10^{-22} \\
 C_{12} &= 1.61307 \times 10^{-26} & C_{14} &= 1.91457 \times 10^{-31}
 \end{aligned}$$

15

9th surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= -7.06471 \times 10^{-11} & C_6 &= 3.77351 \times 10^{-15} \\
 C_8 &= 7.71113 \times 10^{-19} & C_{10} &= 2.18015 \times 10^{-23} \\
 C_{12} &= -2.56756 \times 10^{-28} & C_{14} &= -3.93049 \times 10^{-33}
 \end{aligned}$$

20

11th surface

$$\kappa = 0$$

25

$$\begin{aligned}
 C_4 &= -1.96404 \times 10^{-9} & C_6 &= 8.50314 \times 10^{-14} \\
 C_8 &= -3.99897 \times 10^{-18} & C_{10} &= -7.19500 \times 10^{-23} \\
 C_{12} &= 9.44512 \times 10^{-28} & C_{14} &= -1.72884 \times 10^{-31}
 \end{aligned}$$

5 14th surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= 1.56401 \times 10^{-8} & C_6 &= 1.34769 \times 10^{-13} \\
 C_8 &= -2.96395 \times 10^{-18} & C_{10} &= -1.41277 \times 10^{-21} \\
 C_{12} &= 4.18316 \times 10^{-26} & C_{14} &= -6.92529 \times 10^{-30}
 \end{aligned}$$

10

17th surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= -1.51297 \times 10^{-7} & C_6 &= 8.60926 \times 10^{-12} \\
 C_8 &= -1.71366 \times 10^{-16} & C_{10} &= -4.09208 \times 10^{-20} \\
 C_{12} &= 6.40069 \times 10^{-24} & C_{14} &= -3.08505 \times 10^{-28}
 \end{aligned}$$

15

20th surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= -1.27228 \times 10^{-7} & C_6 &= 2.30534 \times 10^{-13} \\
 C_8 &= 2.42493 \times 10^{-16} & C_{10} &= -7.01920 \times 10^{-20} \\
 C_{12} &= 6.45623 \times 10^{-24} & C_{14} &= -2.48833 \times 10^{-28}
 \end{aligned}$$

20

22nd surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= -3.68686 \times 10^{-8} & C_6 &= 2.41845 \times 10^{-12} \\
 C_8 &= -8.36437 \times 10^{-17} & C_{10} &= 4.79895 \times 10^{-21}
 \end{aligned}$$

25

$$C_{12}=1.98835 \times 10^{-26} \quad C_{14}=-2.10246 \times 10^{-29}$$

24th surface

$$\kappa = 0$$

$$\begin{aligned} 5 \quad C_4 &= 4.95564 \times 10^{-8} & C_6 &= -1.99801 \times 10^{-12} \\ C_8 &= -4.33859 \times 10^{-17} & C_{10} &= 2.96335 \times 10^{-21} \\ C_{12} &= 1.89632 \times 10^{-26} & C_{14} &= -1.60076 \times 10^{-30} \end{aligned}$$

32nd surface

$$10 \quad \kappa = 0$$

$$\begin{aligned} C_4 &= 2.82563 \times 10^{-11} & C_6 &= -2.05877 \times 10^{-15} \\ C_8 &= -7.92881 \times 10^{-19} & C_{10} &= 3.75437 \times 10^{-23} \\ C_{12} &= -7.11351 \times 10^{-28} & C_{14} &= 5.47614 \times 10^{-33} \end{aligned}$$

15 43rd surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -1.18002 \times 10^{-9} & C_6 &= 5.44281 \times 10^{-13} \\ C_8 &= 3.74194 \times 10^{-18} & C_{10} &= 4.03055 \times 10^{-22} \\ C_{12} &= -1.76801 \times 10^{-26} & C_{14} &= 1.60457 \times 10^{-30} \end{aligned}$$

20 Fig. 4 is a diagram showing the transverse aberration in the first example. In the aberration diagram, Y indicates the image height. As apparent from the aberration diagram of Fig. 4, the aberration is well corrected for within the image circle with the radius of 15.5 mm though the very large image-side numerical aperture (NA = 1.04) is secured

25 using the ArF excimer laser light in the dioptric projection optical system with the projection magnification of 1/5 in the first example.

Fig. 5 is an illustration showing the relationship between a shot-area and partial exposure regions in the first example. In the first example, as shown in Fig. 5, a shot-area 51 of $33\text{ mm} \times 26\text{ mm}$ is divided into two partial exposure regions 51a and 51b having the size of $26\text{ mm} \times 16.5\text{ mm}$. Here each of partial exposure regions 51a and 51b is set in the size included in the image circle with the radius of 15.5 mm . In passing, the shot-area 51 has the size not included in the image circle with the radius of 15.5 mm .

In the first example, a still projection exposure is carried out in the first partial exposure region 51a having the size of a half of the shot-area 51, using a first reticle R1 of 6-inch size. Then the first reticle R1 is replaced with a second reticle R2 of 6-inch size. Finally, a still projection exposure is carried out in the second partial exposure region 51b having the size of a half of the shot-area 51, using the second reticle R2. In the first example, since the projection magnification of the projection optical system PL is set at $1/5$ which is smaller than ordinary $1/4$, it is feasible to keep the object-side numerical aperture at a small level in spite of the very large image-side numerical aperture secured, and to well correct for the off-axis aberrations in the still exposure region of the projection optical system PL set in the size of about a half of the shot-area, without causing an increase in the size of lenses.

Although the first example adopts the configuration wherein the interior of the optical path between the projection optical system PL and the wafer W is filled with the medium (deionized water) Lm in order to achieve the large image-side numerical aperture, the execution of the still projection exposures prevents a drop of throughput due to the

intervention of the medium Lm, different from the case of scanning exposure. In this manner, the first example enables the high-resolution projection exposure with high throughput, while securing the large effective image-side numerical aperture ($NA = 1.04$) through the
5 intervention of the high-refractive-index medium Lm in the optical path between the projection optical system PL and the wafer (photosensitive substrate) W, using the dioptric projection optical system PL easy to manufacture and the reticle (mask) of the ordinary size.

[Second Example]

10 Fig. 6 is an illustration showing a lens configuration of a projection optical system according to the second example of the present embodiment. With reference to Fig. 6, the projection optical system PL of the second example is composed of the following components arranged in order from the reticle side: a biconcave lens L1 whose
15 concave surface of aspherical shape is kept toward the wafer; a negative meniscus lens L2 whose concave surface is kept toward the reticle; a negative meniscus lens L3 whose concave surface of aspherical shape is kept toward the reticle; a positive meniscus lens L4 whose concave surface is kept toward the reticle; a biconvex lens L5; a biconvex lens
20 L6; a positive meniscus lens L7 whose convex surface is kept toward the reticle; a positive meniscus lens L8 whose convex surface is kept toward the reticle; a biconcave lens L9; a biconcave lens L10 whose concave surface of aspherical shape is kept toward the reticle; a negative meniscus lens L11 whose concave surface of aspherical shape is kept
25 toward the wafer; a negative meniscus lens L12 whose convex surface of aspherical shape is kept toward the wafer; a lens L13 whose

aspherical surface is kept toward the wafer; a biconvex lens L14; a biconvex lens L15; a positive meniscus lens L16 whose convex surface is kept toward the reticle; a negative meniscus lens L17 whose convex surface is kept toward the reticle; an aperture stop AS; a positive meniscus lens L18 whose concave surface is kept toward the reticle; a positive meniscus lens L19 whose convex surface is kept toward the reticle; a positive meniscus lens L20 whose convex surface is kept toward the reticle; a positive meniscus lens L21 whose convex surface is kept toward the reticle; a positive meniscus lens L22 whose concave surface of aspherical shape is kept toward the wafer; a positive meniscus lens L23 whose convex surface is kept toward the reticle; and a planoconvex lens L24 (boundary lens Lb) whose plane is kept toward the wafer.

In the second example, the optical path between the planoconvex lens L24 as boundary lens Lb and the wafer W is also filled with the medium Lm consisting of deionized water, as in the first example. The lenses L23 and L24 (Lb) are made of fluorite and the other lens components of silica. Table (2) below presents values of specifications of the projection optical system PL in the second example.

TABLE 2

(Principal Specifications)

$$\lambda = 193.306 \text{ nm}$$

$$\beta = 1/6$$

$$NA = 1.04$$

(Specifications of Optical Members)

	Surface No.	r	d	n	Optical Member
		(reticle surface)	47.2707		
	1	-2113.36467	13.0000	1.5603261	(L 1)
5	2*	453.80493	34.2999		
	3	-183.05458	13.5596	1.5603261	(L 2)
	4	-498.57068	19.1820		
	5*	-224.47445	40.1102	1.5603261	(L 3)
	6	-252.37377	1.3804		
10	7	-2482.25164	46.0049	1.5603261	(L 4)
	8	-298.62907	1.1690		
	9	471.69491	44.6807	1.5603261	(L 5)
	10	-31743139.73000	91.3559		
	11	673.69002	51.1596	1.5603261	(L 6)
15	12	-629.89472	1.0000		
	13	258.97666	43.9714	1.5603261	(L 7)
	14	1044.16957	1.0000		
	15	143.74217	49.9057	1.5603261	(L 8)
	16	126.47115	34.6446		
20	17	-4185.00862	13.0000	1.5603261	(L 9)
	18	119.65456	42.1278		
	19*	-141.50576	13.0000	1.5603261	(L 10)
	20	163.61683	14.7204		
	21	747.90268	13.0000	1.5603261	(L 11)
25	22*	185.93581	31.3578		
	23	-220.25186	13.0000	1.5603261	(L 12)

	24*	-1447.38747	1.0000		
	25	3886.00092	29.0911	1.5603261	(L 1 3)
	26*	-3899.69972	3.8815		
	27	11621.97300	60.6998	1.5603261	(L 1 4)
5	28	-189.52544	1.0000		
	29	787.98551	42.7936	1.5603261	(L 1 5)
	30	-729.02232	1.0000		
	31	420.22013	46.9283	1.5603261	(L 1 6)
	32	743.02810	123.0280		
10	33	385.23841	30.6684	1.5603261	(L 1 7)
	34	288.21816	45.4500		
	33	∞	24.1471		(A S)
	36	-530.32540	49.8350	1.5603261	(L 1 8)
	37	-328.54592	1.0000		
15	38	271.23066	56.3549	1.5603261	(L 1 9)
	39	1727.76502	1.0000		
	40	186.72604	45.7017	1.5603261	(L 2 0)
	41	296.60081	1.0009		
	42	166.42204	41.6625	1.5603261	(L 2 1)
20	43	241.72697	1.0000		
	44	152.34470	30.6247	1.5603261	(L 2 2)
	45*	231.02425	1.0000		
	46	109.20982	47.6887	1.5014548	(L 2 3)
	47	174.22298	4.7844		
25	48	233.15627	43.6470	1.5014548	(L 2 4 : L b)
	49	∞	5.0000	1.47	(L m)

(wafer surface)

(Aspherical Data)

2nd surface

5

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -5.89398 \times 10^{-8} & C_6 &= 1.73443 \times 10^{-12} \\ C_8 &= 5.24472 \times 10^{-18} & C_{10} &= -3.86522 \times 10^{-21} \\ C_{12} &= 7.05506 \times 10^{-25} & C_{14} &= -2.32807 \times 10^{-29} \end{aligned}$$

10

5th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -1.41390 \times 10^{-8} & C_6 &= -3.41325 \times 10^{-13} \\ C_8 &= -3.73007 \times 10^{-18} & C_{10} &= -5.71351 \times 10^{-23} \\ C_{12} &= -1.48547 \times 10^{-26} & C_{14} &= 3.67043 \times 10^{-30} \end{aligned}$$

15

19th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -5.54786 \times 10^{-8} & C_6 &= -1.36370 \times 10^{-11} \\ C_8 &= 3.41049 \times 10^{-15} & C_{10} &= -5.24079 \times 10^{-19} \\ C_{12} &= 5.15555 \times 10^{-23} & C_{14} &= -2.51676 \times 10^{-27} \end{aligned}$$

20

22nd surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -4.44688 \times 10^{-8} & C_6 &= -1.46963 \times 10^{-11} \\ C_8 &= 2.74206 \times 10^{-15} & C_{10} &= -3.33399 \times 10^{-19} \\ C_{12} &= 2.40025 \times 10^{-23} & C_{14} &= -8.47472 \times 10^{-28} \end{aligned}$$

25

24th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -6.38951 \times 10^{-8} & C_6 &= 2.40146 \times 10^{-12} \\ C_8 &= -9.96223 \times 10^{-17} & C_{10} &= 1.94408 \times 10^{-21} \\ C_{12} &= 2.46624 \times 10^{-25} & C_{14} &= -1.17831 \times 10^{-29} \end{aligned}$$

26th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= 4.30094 \times 10^{-8} & C_6 &= -8.90706 \times 10^{-13} \\ C_8 &= -5.70322 \times 10^{-17} & C_{10} &= 4.02240 \times 10^{-21} \\ C_{12} &= -1.06448 \times 10^{-25} & C_{14} &= 1.21494 \times 10^{-30} \end{aligned}$$

45th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= 3.18085 \times 10^{-8} & C_6 &= 2.25264 \times 10^{-13} \\ C_8 &= 1.50272 \times 10^{-17} & C_{10} &= 9.64684 \times 10^{-22} \\ C_{12} &= -4.26869 \times 10^{-26} & C_{14} &= 3.72942 \times 10^{-30} \end{aligned}$$

Fig. 7 is an illustration showing the transverse aberration in the second example. In the aberration diagram, Y indicates the image height. As apparent from the aberration diagram of Fig. 7, the aberration is well corrected for in the image circle with the radius of 13.9 mm in the second example, though the very large image-side numerical aperture ($NA = 1.04$) is secured through the use of the ArF excimer laser light in the dioptric projection optical system with the projection magnification of $1/6$.

Fig. 8 is an illustration showing the relationship between a shot-area and partial exposure regions in the second example. In the second example, as shown in Fig. 8, the shot-area 52 of $33\text{ mm} \times 22\text{ mm}$ is divided into two partial exposure regions 52a and 52b having the size of $22\text{ mm} \times 16.5\text{ mm}$. Here each of the partial exposure regions 52a and 52b is set in the size included in the image circle with the radius of 13.9 mm. In passing, the shot-area 52 has the size not included in the image circle with the radius of 13.9 mm.

In the second example, a still projection exposure is carried out in the first partial exposure region 52a with the size of a half of the shot-area 52, using the first reticle R1 of 6-inch size. Next, the first reticle R1 is replaced with the second reticle R2 of 6-inch size. Finally, a still projection exposure is performed in the second partial exposure region 52b having the size of a half of the shot-area 52, using the second reticle R2. Since in the second example the projection magnification of the projection optical system PL is set at $1/6$ smaller than ordinary $1/4$, it is feasible to keep the object-side numerical aperture at a small level in spite of the very large image-side numerical aperture secured, and to well correct for the off-axis aberrations in the still exposure region of the projection optical system PL set in the size of about a half of the shot-area, without causing an increase in the size of lenses.

Although the present example adopts the configuration wherein the interior of the optical path between the projection optical system PL and the wafer W is filled with the medium (deionized water) Lm in order to achieve the large image-side numerical aperture, the execution of the still projection exposures prevents a drop of throughput due to the

intervention of the medium L_m , different from the case of scanning exposure. In this manner, just as the first example, the second example also enables the high-resolution projection exposure with high throughput, while securing the large effective image-side numerical aperture ($NA = 1.04$) through the intervention of the high-refractive-index medium L_m in the optical path between the projection optical system PL and the wafer (photosensitive substrate) W, using the dioptric projection optical system PL easy to manufacture and the reticle (mask) of the ordinary size.

[Third Example]

Fig. 9 is an illustration showing a lens configuration of a projection optical system according to the third example of the present embodiment. With reference to Fig. 9, the projection optical system PL of the third example is composed of the following components arranged in order from the reticle side: a biconcave lens L1 whose concave surface of aspherical shape is kept toward the wafer; a negative meniscus lens L2 whose concave surface is kept toward the reticle; a positive meniscus lens L3 whose concave surface of aspherical shape is kept toward the reticle; a positive meniscus lens L4 whose concave surface is kept toward the reticle; a biconvex lens L5; a positive meniscus lens L6 whose convex surface is kept toward the reticle; a positive meniscus lens L7 whose convex surface is kept toward the reticle; a positive meniscus lens L8 whose convex surface is kept toward the reticle; a negative meniscus lens L9 whose convex surface is kept toward the reticle; a biconcave lens L10 whose concave surface of aspherical shape is kept toward the reticle; a negative meniscus lens L11

whose concave surface of aspherical shape is kept toward the wafer; a negative meniscus lens L12 whose convex surface of aspherical shape is kept toward the wafer; a lens L13 whose aspherical surface is kept toward the wafer; a positive meniscus lens L14 whose concave surface is kept toward the reticle; a biconvex lens L15; a positive meniscus lens L16 whose concave surface is kept toward the reticle; a negative meniscus lens L17 whose convex surface is kept toward the reticle; an aperture stop AS; a positive meniscus lens L18 whose concave surface is kept toward the reticle; a biconvex lens L19; a positive meniscus lens L20 whose convex surface is kept toward the reticle; a positive meniscus lens L21 whose convex surface is kept toward the reticle; a positive meniscus lens L22 whose concave surface of aspherical shape is kept toward the wafer; a positive meniscus lens L23 whose convex surface is kept toward the reticle; and a planoconvex lens L24 (boundary lens Lb) whose plane is kept toward the wafer.

In the third example, the optical path between the planoconvex lens L24 as boundary lens Lb and the wafer W is filled with the medium Lm consisting of deionized water, as in the second example. The lenses L23 and L24 (Lb) are made of fluorite and the other lens components of silica. Table (3) below presents values of specifications of the projection optical system PL in the third example.

TABLE 3

(Principal Specifications)

$$\lambda = 193.306 \text{ nm}$$

$$\beta = 1/4$$

$$NA = 1.1$$

(Specifications of Optical Members)

	Surface No.	r	d	n	Optical Member
		(reticle surface)	43. 2299		
5	1	-1648. 42444	18. 0094	1. 5603261	(L 1)
	2*	155. 60352	53. 8656		
	3	-83. 24602	39. 0000	1. 5603261	(L 2)
	4	-227. 86941	5. 0618		
	5*	-648. 46217	51. 9514	1. 5603261	(L 3)
10	6	-160. 79712	0. 7800		
	7	-1390. 47797	42. 8797	1. 5603261	(L 4)
	8	-268. 83663	0. 7800		
	9	393. 44856	38. 3388	1. 5603261	(L 5)
	10	-24759648. 99000	0. 7800		
15	11	179. 40000	57. 9028	1. 5603261	(L 6)
	12	552. 98755	0. 7800		
	13	158. 85718	37. 9382	1. 5603261	(L 7)
	14	299. 67353	0. 7800		
	15	297. 95802	23. 1595	1. 5603261	(L 8)
20	16	352. 47534	12. 6443		
	17	2975. 86728	13. 5392	1. 5603261	(L 9)
	18	79. 22773	48. 4560		
	19*	-273. 10167	10. 1400	1. 5603261	(L 1 0)
	20	126. 57803	16. 4519		
25	21	677. 57406	10. 1400	1. 5603261	(L 1 1)
	22*	131. 30097	24. 8434		

	23	-459.77022	10.1400	1.5603261	(L 1 2)
	24*	-565.00048	2.7674		
	25	-338.10100	10.1400	1.5603261	(L 1 3)
	26*	-5887.54784	10.1771		
5	27	-755.01102	38.8624	1.5603261	(L 1 4)
	28	-160.32668	0.7800		
	29	1497.37271	36.1113	1.5603261	(L 1 5)
	30	-398.09699	0.7800		
	31	-453.07871	22.4186	1.5603261	(L 1 6)
10	32	-290.48481	0.7800		
	33	335.35995	23.2321	1.5603261	(L 1 7)
	34	305.16493	37.0794		
	35	∞	29.1138		(A S)
	36	-385.77568	33.7858	1.5603261	(L 1 8)
15	37	-232.05704	0.7800		
	38	1914.06318	41.6885	1.5603261	(L 1 9)
	39	-425.72085	0.7800		
	40	217.78624	43.9321	1.5603261	(L 2 0)
	41	693.39425	1.3503		
20	42	146.98824	45.1583	1.5603261	(L 2 1)
	43	329.33948	0.7800		
	44	137.45804	23.0812	1.5603261	(L 2 2)
	45*	163.78004	1.4036		
	46	104.70600	35.6529	1.5014548	(L 2 3)
25	47	208.37760	2.3700		
	48	218.94229	39.0000	1.5014548	(L 2 4 : L b)

49 ∞ 6.2400 1.47 (Lm)
(wafer surface)

(Aspherical Data)

5 2nd surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -2.87434 \times 10^{-7} & C_6 &= 1.77862 \times 10^{-11} \\ C_8 &= -1.51680 \times 10^{-15} & C_{10} &= 1.76703 \times 10^{-19} \\ C_{12} &= -1.12184 \times 10^{-23} & C_{14} &= 5.77460 \times 10^{-28} \end{aligned}$$

10

5th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -1.73314 \times 10^{-8} & C_6 &= 4.42971 \times 10^{-13} \\ C_8 &= -8.97627 \times 10^{-18} & C_{10} &= 4.37986 \times 10^{-22} \\ C_{12} &= -7.75307 \times 10^{-27} & C_{14} &= 5.20902 \times 10^{-32} \end{aligned}$$

15

19th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -2.09048 \times 10^{-7} & C_6 &= 1.52677 \times 10^{-11} \\ C_8 &= -1.03276 \times 10^{-15} & C_{10} &= -5.36272 \times 10^{-22} \\ C_{12} &= 1.70058 \times 10^{-23} & C_{14} &= -2.29651 \times 10^{-27} \end{aligned}$$

20

22nd surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -1.23182 \times 10^{-7} & C_6 &= 3.18273 \times 10^{-13} \\ C_8 &= -8.98342 \times 10^{-16} & C_{10} &= -1.89028 \times 10^{-20} \end{aligned}$$

25

$$C_{12} = 1.25408 \times 10^{-23} \quad C_{14} = -1.36191 \times 10^{-27}$$

24th surface

$$\kappa = 0$$

$$\begin{aligned} 5 \quad C_4 &= -6.70832 \times 10^{-8} & C_6 &= 6.27068 \times 10^{-13} \\ C_8 &= 3.22210 \times 10^{-17} & C_{10} &= -2.68397 \times 10^{-20} \\ C_{12} &= 3.03645 \times 10^{-24} & C_{14} &= -2.93312 \times 10^{-28} \end{aligned}$$

26th surface

$$10 \quad \kappa = 0$$

$$\begin{aligned} C_4 &= 8.42220 \times 10^{-8} & C_6 &= -4.47676 \times 10^{-12} \\ C_8 &= -2.88784 \times 10^{-16} & C_{10} &= 3.66491 \times 10^{-20} \\ C_{12} &= -1.87557 \times 10^{-24} & C_{14} &= 2.37260 \times 10^{-29} \end{aligned}$$

15 45th surface

$$\kappa = 0$$

$$\begin{aligned} C_4 &= -4.71348 \times 10^{-8} & C_6 &= 1.88759 \times 10^{-12} \\ C_8 &= 1.21807 \times 10^{-16} & C_{10} &= -1.16571 \times 10^{-20} \\ C_{12} &= 5.85852 \times 10^{-25} & C_{14} &= -1.02599 \times 10^{-30} \end{aligned}$$

20 Fig. 10 is an illustration showing the transverse aberration in the third example. In the aberration diagram, Y indicates the image height. As apparent from the aberration diagram of Fig. 10, the aberration is well corrected for in the image circle with the radius of 10.7 mm in the third example, though the very large image-side numerical aperture (NA = 1.1) is secured through the use of the ArF excimer laser light in the

25 dioptric projection optical system with the projection magnification of

1/4.

Fig. 11 is an illustration showing the relationship between a shot-area and partial exposure regions in the third example. In the third example, as shown in Fig. 11, the shot-area 53 of 33 mm × 26 mm is divided into four partial exposure regions 53a, 53b, 53c, and 53d having the size of 16.5 mm × 13 mm. Here each of the partial exposure regions 53a-53d is set in the size included in the image circle with the radius of 10.7 mm. In passing, the shot-area 53 has the size not included in the image circle with the radius of 10.7 mm.

In the third example, a still projection exposure is performed in the first partial exposure region 53a with the size of a quarter of the shot-area 53, using the first reticle R1 of 6-inch size. Next, the first reticle R1 is replaced with the second reticle R2 of 6-inch size, and a still projection exposure is performed in the second partial exposure region 53b having the size of a quarter of the shot-area 53, using the second reticle R2. Furthermore, the second reticle R2 is replaced with the third reticle R3 of 6-inch size and a still projection exposure is performed in the third partial exposure region 53c having the size of a quarter of the shot-area 53, using the third reticle R3. Finally, the third reticle R3 is replaced with the fourth reticle R4 of 6-inch size and a still projection exposure is performed in the fourth partial exposure region 53d having the size of a quarter of the shot-area 53, using the fourth reticle R4.

In the third example the projection magnification of the projection optical system PL is set at ordinary 1/4, and the still exposure region of the projection optical system PL is set in the size of about a

quarter of the shot-area; therefore, it is feasible to well correct for the off-axis aberrations in the still exposure region without causing an increase in the size of lenses, though the very large image-side numerical aperture is secured. Although the present example adopts the configuration wherein the interior of the optical path between the projection optical system PL and the wafer W is filled with the medium (deionized water) Lm in order to achieve the large image-side numerical aperture, the execution of the still projection exposures prevents a drop of throughput due to the intervention of the medium Lm, different from the case of scanning exposure. In this manner, just as the first example and the second example, the third example also enables the high-resolution projection exposure with high throughput, while securing the large effective image-side numerical aperture ($NA = 1.1$) through the intervention of the high-refractive-index medium Lm in the optical path between the projection optical system PL and the wafer (photosensitive substrate) W, using the dioptric projection optical system PL easy to manufacture and the reticle (mask) of the ordinary size.

In each of the above-described examples one shot-area is equally divided into two or four partial exposure regions, but it is also possible to perform the so-called partly overlapping exposure in a state in which two partial exposure regions adjacent to each other overlap in part with each other. In each of the above-described examples one shot-area is divided into two or four partial exposure regions and one projection exposure is performed for each partial exposure region; however, it is also possible to perform double exposures for at least one partial exposure region.

In each of the above-described examples the still projection exposure is performed for each partial exposure region, but it is also possible to perform a scan exposure of a reticle pattern in each partial exposure region while moving the reticle and wafer relative to the projection optical system. In each of the above-described examples the projection exposure for each partial exposure region is performed using the dioptric projection optical system, but, without having to be limited to this, it is also possible to perform the projection exposure for each partial exposure region, for example, by use of a catadioptric projection optical system.

In the examples presented below, the medium L_m interposed between the boundary lens L_b and the wafer W is pure water having the refractive index of 1.43664 for the exposure light in the fourth example, and pure water having the refractive index of 1.43600 for the exposure light in the fifth example.

[Fourth Example]

Fig. 12 is an illustration showing a lens configuration of a projection optical system according to the fourth example of the present embodiment. With reference to Fig. 12, the projection optical system PL of the fourth example is composed of the following lens units arranged in order from the reticle side: a first lens unit G1 having a positive refracting power; a second lens unit G2 having a negative refracting power; a third lens unit G3 having a positive refracting power; a fourth lens unit G4 having a negative refracting power; a fifth lens unit G5 having a positive refracting power; an aperture stop AS; and a sixth lens unit G6 having a positive refracting power.

The first lens unit G1 is composed of the following components arranged in order from the reticle side: a plane-parallel plate P1; a planoconcave lens L11 whose plane is kept toward the reticle; a biconvex lens L12; and a biconvex lens L13. The second lens unit G2 is composed of the following components arranged in order from the reticle side: a negative meniscus lens L21 whose concave surface of aspherical shape is kept toward the wafer; a biconcave lens L22; a biconcave lens L23; and a negative meniscus lens L24 whose concave surface is kept toward the reticle.

The third lens unit G3 is composed of the components arranged in order from the reticle side: a positive meniscus lens L31 whose concave surface of aspherical shape is kept toward the reticle; a positive meniscus lens L32 whose concave surface is kept toward the reticle; a biconvex lens L33; a positive meniscus lens L34 whose convex surface is kept toward the reticle; a positive meniscus lens L35 whose convex surface is kept toward the reticle; and a positive meniscus lens L36 whose concave surface of aspherical shape is kept toward the wafer. The fourth lens unit G4 is composed of the following components arranged in order from the reticle side: a negative meniscus lens L41 whose convex surface is kept toward the reticle; a biconcave lens L42 whose concave surface of aspherical shape is kept toward the wafer; a biconcave lens L43 whose concave surface of aspherical shape is kept toward the wafer; and a biconcave lens L44 whose concave surface of aspherical shape is kept toward the wafer.

The fifth lens unit G5 is composed of the following components arranged in order from the reticle side: a positive meniscus lens L51

whose concave surface is kept toward the reticle; a positive meniscus lens L52 whose concave surface is kept toward the reticle; and a biconvex lens L53. The sixth lens unit G6 is composed of the following components arranged in order from the reticle side: a positive meniscus lens L61 whose convex surface is kept toward the reticle; a positive meniscus lens L62 whose convex surface is kept toward the reticle; a positive meniscus lens L63 whose concave surface of aspherical shape is kept toward the wafer; a positive meniscus lens L64 whose concave surface of aspherical shape is kept toward the wafer; and a planoconvex lens L65 (boundary lens Lb) whose plane is kept toward the wafer.

In the fourth example, the optical path between the planoconvex lens L65 as boundary lens Lb and the wafer W is filled with the medium Lm consisting of pure water. Only the planoconvex lens L65 is made of fluorite and the other lens components are made of silica.

Table (4) below presents values of specifications of the projection optical system PL in the fourth example. In Table (4), λ indicates the center wavelength of the exposure light, β the projection magnification (the imaging magnification of the entire system), NA the image-side (wafer-side) numerical aperture, and Y_m the maximum image height. Each surface number represents an order of a surface from the reticle side, r a radius of curvature of each surface (in the case of an aspherical surface, a radius of curvature at the apex: mm), d an axial spacing or surface separation of each surface (mm), and n a refractive index for the center wavelength. The notations in Table (4) also apply to Table (5) hereinafter.

TABLE 4

(Principal Specifications)

$$\lambda = 193.306 \text{ nm}$$

$$\beta = 1/8$$

5
$$\text{NA} = 1.2$$

$$Y_m = 10.5 \text{ mm}$$

(Specifications of Optical Members)

	Surface No.	r	d	n	Optical Member
		(reticle surface)	50.0000		
10	1	∞	8.0000	1.5603261	(P 1)
	2	∞	1.0000		
	3	∞	14.0000	1.5603261	(L 1 1)
	4	5801.10144	1.0000		
	5	274.57869	39.8653	1.5603261	(L 1 2)
15	6	-459.16446	1.0000		
	7	1390.27385	20.0564	1.5603261	(L 1 3)
	8	-868.62766	1.0000		
	9	465.65065	14.0000	1.5603261	(L 2 1)
	10*	173.96720	24.0693		
20	11	-731.07113	14.0000	1.5603261	(L 2 2)
	12	235.12498	39.4555		
	13	-141.54085	14.0000	1.5603261	(L 2 3)
	14	722.38474	37.8810		
	15	-157.78699	21.8588	1.5603261	(L 2 4)
25	16	-280.56758	1.0000		
	17*	-326.76108	21.9918	1.5603261	(L 3 1)

	18	-244.25456	1.0000		
	19	-449.50039	56.4826	1.5603261	(L 3 2)
	20	-183.11101	1.0000		
	21	2302.89247	51.2616	1.5603261	(L 3 3)
5	22	-411.55543	1.0000		
	23	371.46326	48.7816	1.5603261	(L 3 4)
	24	9503.36549	1.0000		
	25	235.11152	39.9014	1.5603261	(L 3 5)
	26	421.36614	1.0000		
10	27	154.86823	61.6838	1.5603261	(L 3 6)
	28*	465.72497	1.5047		
	29	501.43967	16.9978	1.5603261	(L 4 1)
	30	91.81381	47.4329		
	31	-5363.84429	14.0000	1.5603261	(L 4 2)
15	32*	113.46256	54.7519		
	33	-113.22450	14.0000	1.5603261	(L 4 3)
	34*	171.05713	42.4704		
	35	-2480.75152	20.3116	1.5603261	(L 4 4)
	36*	1352.94197	10.7376		
20	37	-1754.53968	37.5345	1.5603261	(L 5 1)
	38	-279.22390	1.0000		
	39	-863.35259	57.3985	1.5603261	(L 5 2)
	40	-209.74679	1.0000		
	41	441.49020	48.9491	1.5603261	(L 5 3)
25	42	-31363.74644	130.3080		
	43	∞	25.8952		(A S)

	44	304.24875	43.3437	1.5603261	(L 6 1)
	45	796.93838	1.0000		
	46	197.10040	65.0278	1.5603261	(L 6 2)
	47	539.90461	1.0000		
5	48	140.41439	59.2217	1.5603261	(L 6 3)
	49*	424.51849	1.0000		
	50	92.87520	50.0000	1.5603261	(L 6 4)
	51*	106.82152	1.0000		
	52	89.56390	40.9132	1.5014548	(L 6 5 : L b)
10	53	∞	3.0000	1.43664	(L m)

(wafer surface)

(Aspherical Data)

10th surface

15

$\kappa = 0$

$$\begin{aligned}
 C_4 &= -3.70154 \times 10^{-8} & C_6 &= -7.54540 \times 10^{-13} \\
 C_8 &= -1.16366 \times 10^{-17} & C_{10} &= 9.55608 \times 10^{-22} \\
 C_{12} &= -6.37962 \times 10^{-26} & C_{14} &= 1.01247 \times 10^{-29}
 \end{aligned}$$

20

17th surface

$\kappa = 0$

$$\begin{aligned}
 C_4 &= -1.74641 \times 10^{-8} & C_6 &= 1.67557 \times 10^{-13} \\
 C_8 &= -4.43667 \times 10^{-18} & C_{10} &= 2.27983 \times 10^{-22} \\
 C_{12} &= -4.73178 \times 10^{-27} & C_{14} &= 3.84644 \times 10^{-31}
 \end{aligned}$$

25

28th surface

$$\kappa = 0$$

$$C_4 = -1.48540 \times 10^{-8}$$

$$C_6 = 1.37389 \times 10^{-12}$$

$$C_8 = -7.33575 \times 10^{-17}$$

$$C_{10} = 2.78286 \times 10^{-21}$$

$$C_{12} = -6.35060 \times 10^{-26}$$

$$C_{14} = 4.99896 \times 10^{-31}$$

5

32nd surface

$$\kappa = 0$$

$$C_4 = -9.75576 \times 10^{-8}$$

$$C_6 = -8.64616 \times 10^{-12}$$

$$C_8 = -1.88917 \times 10^{-16}$$

$$C_{10} = -4.12721 \times 10^{-20}$$

10

$$C_{12} = 2.39206 \times 10^{-24}$$

$$C_{14} = -1.23126 \times 10^{-27}$$

$$C_{16} = 4.51071 \times 10^{-32}$$

34th surface

$$\kappa = 0$$

15

$$C_4 = -6.26183 \times 10^{-8}$$

$$C_6 = -1.64882 \times 10^{-12}$$

$$C_8 = 4.65519 \times 10^{-17}$$

$$C_{10} = 1.00317 \times 10^{-20}$$

$$C_{12} = -6.91878 \times 10^{-25}$$

$$C_{14} = 7.21109 \times 10^{-30}$$

36th surface

20

$$\kappa = 0$$

$$C_4 = 8.44783 \times 10^{-9}$$

$$C_6 = -3.53948 \times 10^{-13}$$

$$C_8 = 2.80062 \times 10^{-18}$$

$$C_{10} = 5.31087 \times 10^{-23}$$

$$C_{12} = -5.69081 \times 10^{-27}$$

$$C_{14} = 2.11477 \times 10^{-32}$$

25

49th surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= 4.19765 \times 10^{-8} & C_6 &= -3.95821 \times 10^{-13} \\
 C_8 &= 1.25706 \times 10^{-17} & C_{10} &= 9.21384 \times 10^{-22} \\
 C_{12} &= -4.77212 \times 10^{-26} & C_{14} &= 1.73402 \times 10^{-30}
 \end{aligned}$$

5 51st surface

$$\kappa = 0$$

$$\begin{aligned}
 C_4 &= 1.41379 \times 10^{-7} & C_6 &= 2.76603 \times 10^{-11} \\
 C_8 &= 1.95695 \times 10^{-15} & C_{10} &= 2.49670 \times 10^{-19} \\
 C_{12} &= 8.01029 \times 10^{-23} & C_{14} &= 5.62960 \times 10^{-27}
 \end{aligned}$$

10

(Values corresponding to Conditions)

$$L2 = 291.4 \text{ mm}$$

$$LA = 1250 \text{ mm}$$

$$P2 = 30.03 \text{ mm}$$

15 $PX = 326.5 \text{ mm}$

$$D4 = 141.13 \text{ mm}$$

$$D0 = 168.0 \text{ mm}$$

$$(1) L2/LA = 0.233$$

$$(2) P2/PX = 0.092$$

20 $(3) D4/D0 = 0.840$

Fig. 13 is a diagram showing the transverse aberration in the fourth example. In the aberration diagram, Y indicates the image height. As apparent from the aberration diagram of Fig. 13, the aberration is well corrected for within the image circle with the radius (maximum image height) of 10.5 mm though the very large image-side numerical aperture (NA = 1.2) is secured using the ArF excimer laser

light in the dioptric projection optical system with the projection magnification of $1/8$ in the fourth example.

[Fifth Example]

Fig. 14 is an illustration showing a lens configuration of a projection optical system according to the fifth example of the present embodiment. With reference to Fig. 14, the projection optical system PL of the fifth example is composed of the following lens units arranged in order from the reticle side: a first lens unit G1 having a negative refracting power; a second lens unit G2 having a positive refracting power; a third lens unit G3 having a negative refracting power; a fourth lens unit G4 having a positive refracting power; an aperture stop AS; and a fifth lens unit G5 having a positive refracting power.

The first lens unit G1 is composed of the following components arranged in order from the reticle side: a plane-parallel plate P1; a biconcave lens L11 whose concave surface of aspherical shape is kept toward the wafer; and a negative meniscus lens L12 whose concave surface of aspherical shape is kept toward the reticle. The second lens unit G2 is composed of the following components arranged in order from the reticle side: a positive meniscus lens L21 whose concave surface is kept toward the reticle; a positive meniscus lens L22 whose concave surface is kept toward the reticle; a biconvex lens L23 whose convex surface of aspherical shape is kept toward the wafer; a positive meniscus lens L24 whose convex surface is kept toward the reticle; and a positive meniscus lens L25 whose convex surface is kept toward the reticle.

The third lens unit G3 is composed of the following components

arranged in order from the reticle side: a biconcave lens L31; a negative meniscus lens L32 whose concave surface is kept toward the reticle; and a biconcave lens L33 whose concave surface of aspherical shape is kept toward the wafer. The fourth lens unit G4 is composed of the following components arranged in order from the reticle side: a positive meniscus lens L41 whose concave surface of aspherical shape is kept toward the reticle; a positive meniscus lens L42 whose concave surface of aspherical shape is kept toward the wafer; a positive meniscus lens L43 whose convex surface is kept toward the reticle; and a negative meniscus lens L44 whose convex surface is kept toward the reticle.

The fifth lens unit G5 is composed of the following components arranged in order from the reticle side: a positive meniscus lens L51 whose concave surface is kept toward the reticle; a biconvex lens L52; a positive meniscus lens L53 whose convex surface is kept toward the reticle; a positive meniscus lens L54 whose convex surface is kept toward the reticle; a positive meniscus lens L55 whose concave surface of aspherical shape is kept toward the wafer; a negative meniscus lens L56 whose convex surface is kept toward the reticle; and a planoconvex lens L57 (boundary lens Lb) whose plane is kept toward the wafer.

In the fifth example the optical path between the planoconvex lens L57 as boundary lens Lb and the wafer W is filled with the medium Lm consisting of pure water. Only the negative meniscus lens L56 and planoconvex lens L57 are made of fluorite and the other lens components of silica. Table (5) below presents values of specifications of the projection optical system PL in the fifth example.

TABLE 5

(Principal Specifications)

$$\lambda = 193.306 \text{ nm}$$

$$\beta = 1/8$$

$$NA = 1.1$$

$$5 \quad Y_m = 10.5 \text{ mm}$$

(Specifications of Optical Members)

	Surface No.	r	d	n	Optical Member
		(reticle surface)	50.000		
10	1	∞	8.000	1.5603261	(P 1)
	2	∞	5.852		
	3	-2113.365	14.000	1.5603261	(L 1 1)
	4*	392.563	82.347		
	5*	-153.929	14.585	1.5603261	(L 1 2)
15	6	-394.912	2.821		
	7	-468.749	24.661	1.5603261	(L 2 1)
	8	-303.970	4.731		
	9	-2515.151	42.207	1.5603261	(L 2 2)
	10	-309.040	3.752		
20	11	912.984	47.173	1.5603261	(L 2 3)
	12*	-468.749	1.000		
	13	213.298	47.130	1.5603261	(L 2 4)
	14	621.048	1.000		
	15	207.549	39.109	1.5603261	(L 2 5)
25	16	398.158	81.085		
	17	-415.296	14.000	1.5603261	(L 3 1)

	18	85.260	42.810		
	19	-102.120	35.159	1.5603261	(L 3 2)
	20	-103.431	21.454		
	21	-91.135	14.157	1.5603261	(L 3 3)
5	22*	165.940	44.380		
	23*	-193.036	53.016	1.5603261	(L 4 1)
	24	-131.393	43.188		
	25*	-1536.216	60.000	1.5603261	(L 4 2)
	26	-218.584	1.059		
10	27	464.954	32.460	1.5603261	(L 4 3)
	28	1937.918	37.933		
	29	1041.991	29.971	1.5603261	(L 4 4)
	30	427.093	34.141		
	31	∞	27.275		(A S)
15	32	-1066.707	42.356	1.5603261	(L 5 1)
	33	-326.104	1.078		
	34	631.260	60.000	1.5603261	(L 5 2)
	35	-489.634	1.000		
	36	187.612	44.290	1.5603261	(L 5 3)
20	37	386.150	1.000		
	38	140.054	38.790	1.5603261	(L 5 4)
	39	236.715	1.000		
	40	134.236	19.527	1.5603261	(L 5 5)
	41*	131.000	1.000		
25	42	122.637	30.971	1.5014548	(L 5 6)
	43	63.462	1.022		

44 62.543 46.511 1.5014548 (L 5 7 : L b)

45 ∞ 1.000 1.43600 (L m)

(wafer surface)

5 (Aspherical Data)

4th surface

$$\kappa = 0$$

$$C_4 = -6.87058 \times 10^{-8} \quad C_6 = 1.98337 \times 10^{-12}$$

$$C_8 = -2.33418 \times 10^{-17} \quad C_{10} = 4.28841 \times 10^{-21}$$

$$10 \quad C_{12} = -1.88289 \times 10^{-25} \quad C_{14} = 1.05516 \times 10^{-29}$$

5th surface

$$\kappa = 0$$

$$C_4 = 8.21473 \times 10^{-9} \quad C_6 = 5.90186 \times 10^{-13}$$

$$15 \quad C_8 = 2.81237 \times 10^{-17} \quad C_{10} = 1.57429 \times 10^{-21}$$

$$C_{12} = -1.01146 \times 10^{-25} \quad C_{14} = 4.09058 \times 10^{-30}$$

12th surface

$$\kappa = 0$$

$$20 \quad C_4 = -1.35709 \times 10^{-8} \quad C_6 = 1.56240 \times 10^{-15}$$

$$C_8 = 9.48076 \times 10^{-19} \quad C_{10} = 5.36314 \times 10^{-22}$$

$$C_{12} = 0 \quad C_{14} = 0$$

22nd surface

$$25 \quad \kappa = 0$$

$$C_4 = -8.62552 \times 10^{-8} \quad C_6 = -3.31660 \times 10^{-12}$$

$$C_8 = 3.60806 \times 10^{-16}$$

$$C_{10} = -2.06842 \times 10^{-20}$$

$$C_{12} = 4.96281 \times 10^{-25}$$

$$C_{14} = 4.51047 \times 10^{-31}$$

23rd surface

5

$$\kappa = 0$$

$$C_4 = -2.42730 \times 10^{-8}$$

$$C_6 = -9.37917 \times 10^{-14}$$

$$C_8 = 9.55217 \times 10^{-17}$$

$$C_{10} = 5.22545 \times 10^{-21}$$

$$C_{12} = 3.80044 \times 10^{-25}$$

$$C_{14} = 3.98450 \times 10^{-29}$$

10

25th surface

$$\kappa = 0$$

$$C_4 = -2.28538 \times 10^{-8}$$

$$C_6 = 2.70616 \times 10^{-14}$$

$$C_8 = -4.54050 \times 10^{-18}$$

$$C_{10} = -7.42942 \times 10^{-24}$$

$$C_{12} = -1.22807 \times 10^{-27}$$

$$C_{14} = -2.98334 \times 10^{-32}$$

15

41st surface

$$\kappa = 0$$

$$C_4 = -4.41623 \times 10^{-8}$$

$$C_6 = -1.35429 \times 10^{-12}$$

$$C_8 = 1.59382 \times 10^{-17}$$

$$C_{10} = -1.00707 \times 10^{-21}$$

20

$$C_{12} = -2.48318 \times 10^{-25}$$

$$C_{14} = -8.65436 \times 10^{-30}$$

(Values corresponding to Conditions)

$$L2 = 289.5 \text{ mm}$$

$$LA = 1250 \text{ mm}$$

25

$$P3 = 56.91 \text{ mm}$$

$$PX = 320.7 \text{ mm}$$

$$D3 = 112.25 \text{ mm}$$

$$D0 = 168.0 \text{ mm}$$

$$(1) L2/LA = 0.232$$

$$(2) P3/PX = 0.177$$

$$5 \quad (3) D3/D0 = 0.668$$

Fig. 15 is a diagram showing the transverse aberration in the fifth example. In the aberration diagram, Y indicates the image height. As apparent from the aberration diagram of Fig. 15, the aberration is well corrected for within the image circle with the radius (maximum image height) of 10.5 mm though the very large image-side numerical aperture (NA = 1.1) is secured using the ArF excimer laser light in the dioptric projection optical system with the projection magnification of 1/8 in the fifth example, as in the fourth example.

Fig. 16 is an illustration showing the relationship between a shot-area and partial exposure regions in the fourth and fifth examples. In the fourth and fifth examples, as shown in Fig. 16, a shot-area (corresponding to one chip) 7 of 33 mm × 26 mm is divided into four partial exposure regions 7a, 7b, 7c, and 7d having the size of 16.5 mm × 13 mm. Here each of the partial exposure regions 7a-7d is substantially included in the image circle with the radius of 10.5 mm.

In the fourth and fifth examples, a still projection exposure is performed in the first partial exposure region 7a having the size of a quarter of shot-area 7, using the first reticle R1 of 6-inch size. Then the first reticle R1 is replaced with the second reticle R2 of 6-inch size and a still projection exposure is performed in the second partial exposure region 7b having the size of a quarter of shot-area 7, using the

second reticle R2. Furthermore, the second reticle R2 is replaced with the third reticle R3 of 6-inch size and a still projection exposure is performed in the third partial exposure region 7c having the size of a quarter of shot-area 7, using the third reticle R3. Finally, the third
5 reticle R3 is replaced with the fourth reticle R4 of 6-inch size and a still projection exposure is performed in the fourth partial exposure region 7d having the size of a quarter of shot-area 7, using the fourth reticle R4.

In the fourth and fifth examples, the projection magnification of the projection optical system PL is set at $1/8$ smaller than normal $1/4$ and the still exposure region of the projection optical system PL is set to
10 the size of about a quarter of the shot-area; therefore, the object-side numerical aperture can be kept at a small level in spite of the very large image-side numerical aperture secured. As a result, it is feasible to well correct for the off-axis aberrations such as coma and, in turn, to
15 secure the relatively large effective imaging area, without causing an increase in the size of lenses.

The above examples employ the configuration wherein the interior of the optical path between the projection optical system PL and the wafer W is filled with the medium (pure water) L_m in order to
20 achieve the large image-side numerical aperture, but the execution of the still projection exposures prevents a drop of throughput due to the intervention of the medium L_m , different from the case of scanning exposure. In this manner, the fourth and fifth examples enable the high-resolution projection exposure with high throughput, while
25 securing the large effective image-side numerical aperture ($NA = 1.2$ or 1.1) through the intervention of the high-refractive-index medium L_m in

the optical path between the projection optical system PL and the wafer (photosensitive substrate) W, using the dioptric projection optical system PL easy to manufacture and the reticle (mask) of the ordinary size.

5 The above description was given with focus on one shot-area 7 and a partial exposure step of performing a still projection exposure was repeated for the partial exposure regions 7a-7d thereof. In practice, however, partial exposure steps are repeated for a plurality of shot-areas on one wafer W. Specifically, as shown in Figs. 17A to 17D, first
10 partial exposure regions (hatched portions in Fig. 17A) in a plurality of shot-areas on a wafer W are successively exposed, the mask is replaced with another, and thereafter second partial exposure regions (hatched portions in Fig. 17B) in the plurality of shot-areas are successively exposed. Then the mask is replaced with another and thereafter third
15 partial exposure regions (hatched portions in Fig. 17C) in the plurality of shot-areas are successively exposed. Furthermore, the mask is replaced with another and fourth partial exposure regions (hatched portions in Fig. 17D) in the plurality of shot-areas are successively exposed.

20 In the example of Figs. 17A-17D, the third or fourth partial exposure regions are located between the plurality of first partial exposure regions in the plurality of shot-areas; i.e., the plurality of first partial exposure regions in the plurality of shot-areas are formed with a space (or the plurality of first partial exposure regions do not adjoin
25 each other). Since the exposure regions formed by the previous exposure are located away from the exposure regions formed by the

subsequent exposure as described above, it becomes feasible to avoid influence of heat or the like due to the previous exposure, in the subsequent exposure.

5 In the fourth and fifth examples described above, one shot-area is equally divided into four partial exposure regions, but it is also possible to perform the so-called partly overlapping exposure in a state in which two partial exposure regions adjacent to each other overlap in part with each other. In the above-described fourth and fifth examples, one shot-area is divided into four partial exposure regions and one
10 projection exposure is carried out for each partial exposure region; however, it is also possible to perform double exposures for at least one partial exposure region. The above-described fourth and fifth examples involve performing the still projection exposure for each partial exposure region, but it is also possible to perform a scan
15 exposure of a reticle pattern in each partial exposure region while moving the reticle and wafer relative to the projection optical system.

In the above-described fourth example, only the planoconvex lens L65 is made of fluorite, but the optical system is preferably constructed so as to include a pair of fluorite lenses, for example, by
20 dividing the planoconvex lens L65 into two lenses or by forming the positive meniscus lens L64 of fluorite. In this configuration, influence of birefringence specific to fluorite can be reduced by properly setting the relation of orientations of crystal axes of the pair of fluorite lenses. For the technique of reducing the influence of birefringence specific to
25 fluorite by properly setting the orientation relation of crystal axes of the pair of fluorite lenses, reference should be made, for example, to

WO2003/007045 (or U.S. Published Patent Application US2003/0053036A) and others.

The exposure apparatus of the aforementioned embodiment can produce microdevices (semiconductor devices, image pickup devices, liquid-crystal display devices, thin-film magnetic heads, etc.) by illuminating the reticle (mask) by the illumination device (illumination step) and performing an exposure of a transcription pattern formed on the mask, onto the photosensitive substrate by the projection optical system (exposure step). An example of a method for producing semiconductor devices as microdevices by forming a predetermined circuit pattern on a wafer or the like as a photosensitive substrate by use of the exposure apparatus of the present embodiment will be described below with reference to the flowchart of Fig. 18.

First, step 301 in Fig. 18 is to form an evaporated metal film on each of wafers in one lot. Next step 302 is to apply a photoresist onto the metal film on each of the wafers in the lot. Thereafter, step 303 is to sequentially perform an exposure to transcribe an image of a pattern on a mask into each shot-area on each of the wafers in the lot through the projection optical system, using the exposure apparatus of the present embodiment. Step 304 thereafter is to perform development of the photoresist on each of the wafers in the lot, and next step 305 is to perform etching with the resist pattern as a mask on each of the wafers in the lot to form a circuit pattern corresponding to the pattern on the mask, in each shot-area on each wafer.

Thereafter, through formation of circuit patterns of upper layers and others, the devices such as semiconductor devices are produced.

The semiconductor device production method described above permits us to obtain the semiconductor devices with an extremely fine circuit pattern at high throughput. Step 301 to step 305 are to perform the respective steps of evaporation of metal on the wafers, application of the resist onto the metal film, exposure, development, and etching, but it is needless to mention that the method may be so arranged that, prior to these steps, a silicon oxide film is formed on the wafer and thereafter the resist is applied onto the silicon oxide film, followed by the respective steps of exposure, development, etching, and so on.

The exposure apparatus of the present embodiment can also produce a liquid-crystal display device as a microdevice by forming predetermined patterns (circuit pattern, electrode pattern, etc.) on a plate (glass substrate). An example of a method of this production will be described below with reference to the flowchart of Fig. 19. In Fig. 19, pattern forming step 401 is to execute a so-called photolithography step of performing an exposure to transcribe a pattern of a mask onto a photosensitive substrate (a glass substrate coated with a resist or the like) by the exposure apparatus of the present embodiment. This photolithography step results in forming the predetermined pattern including a number of electrodes and others on the photosensitive substrate. Thereafter, the exposed substrate is processed through respective steps of development, etching, resist removal, and so on to form a predetermined pattern on the substrate, and is then transferred to next color filter forming step 402.

Next, the color filter forming step 402 is to form a color filter in a configuration wherein a number of sets of three dots corresponding to

R (Red), G (Green), and B (Blue) are arrayed in a matrix, or in a configuration wherein a plurality of sets of filters of three stripes of R, G, and B are arranged in the direction of horizontal scan lines. After the color filter forming step 402, cell assembly step 403 is then executed. The cell assembly step 403 is to assemble a liquid crystal panel (liquid crystal cell), using the substrate with the predetermined pattern obtained in the pattern forming step 401, the color filter obtained in the color filter forming step 402, and so on. In the cell assembly step 403, for example, a liquid crystal is poured into the space between the substrate with the predetermined pattern obtained in the pattern forming step 401 and the color filter obtained in the color filter forming step 402, thereby producing a liquid crystal panel (liquid crystal cell).

Module assembly step 404 thereafter is to attach each of components such as an electric circuit, a backlight, etc. for display operation of the assembled liquid crystal panel (liquid crystal cell), thereby completing a liquid-crystal display device. The production method of the liquid-crystal display device described above permits liquid-crystal display devices with the extremely fine circuit pattern to be produced at high throughput.

The above embodiment uses the ArF excimer laser source, but, without having to be limited to this, it is also possible to use other appropriate light sources such as the F₂ laser source.

Since the present embodiment uses the ArF excimer laser light as the exposure light as described above, pure water is supplied as a liquid for liquid immersion exposure. Pure water is easily available in large quantity in semiconductor manufacturing facilities and others and

has the advantage of no adverse effect on the photoresist on the substrate (wafer), the optical elements (lenses), and others. Since pure water has no adverse effect on environments and contains an extremely low amount of impurities, we can also expect the action of cleaning the surface of the substrate and the surface of the optical element located on the distal end surface of the projection optical system.

Pure water (water) is said to have the refractive index n of about 1.44 for the exposure light of the wavelength of approximately 193 nm. In the case where the ArF excimer laser light (wavelength 193 nm) is used as a light source of exposure light, the wavelength is reduced to $1/n$, i.e., about 134 nm on the substrate to achieve high resolution. Furthermore, the depth of focus is increased to about n times or about 1.44 times that in air.

The liquid can be another liquid that is transparent to the exposure light, has the refractive index as high as possible, and is stable against the projection optical system and the photoresist on the surface of the substrate.

Where the F_2 laser light is used as the exposure light, the liquid can be a fluorinated liquid, for example, such as fluorinated oils and perfluorinated polyethers (PFPE), which can transmit the F_2 laser light.

The aforementioned embodiment adopts the configuration wherein the liquid is locally filled between the projection optical system PL and the substrate P, or the configuration wherein the liquid chamber in a predetermined depth is formed on the stage and wherein the substrate is held therein, but the present invention can also be applied to liquid immersion exposure apparatus arranged to move the stage

holding the substrate to be exposed, in a liquid chamber. The structure and exposure operation of the liquid immersion exposure apparatus for moving the stage holding the substrate to be exposed, in the liquid chamber are disclosed, for example, in Japanese Patent Application
5 Laid-Open No. 6-124873.

The present invention is also applicable to exposure apparatus of a twin stage type. The structure and exposure operation of the twin stage type exposure apparatus are disclosed, for example, in Japanese Patent Applications Laid-Open No. 10-163099 and No. 10-214783
10 (corresponding to U.S. Pat. No. 6,341,007, No. 6,400,441, No. 6,549,269, and No. 6,590,634), JP-A-2000-505958 (corresponding to U.S. Pat. No. 5,969,441), or U.S. Pat. No. 6,208,407.

When the liquid immersion method is applied as described above, the numerical aperture NA of the projection optical system can
15 be 0.9 to 1.3. In cases where the numerical aperture NA of the projection optical system is so large as described, use of randomly polarized light conventionally applied as the exposure light can degrade the imaging performance by virtue of its polarization effect, and it is thus desirable to use polarized illumination. A preferred configuration
20 in those cases is such that linearly polarized illumination is effected in alignment with the longitudinal direction of line patterns of line-and-space patterns on the mask (reticle) so that the s-polarized component (TE polarization component), i.e., diffracted light in the polarization direction along the longitudinal direction of the line patterns is more
25 emitted from the patterns of the mask (reticle). When the liquid fills the space between the projection optical system PL and the resist

applied on the surface of the substrate P, the transmittance becomes higher on the resist surface for the diffracted light of the s-polarized component (TE polarization component) contributing to improvement in contrast than in the case where air (gas) fills the space between the projection optical system PL and the resist applied on the surface of the substrate P. For this reason, the high imaging performance can also be achieved even in the case where the numerical aperture NA of the projection optical system exceeds 1.0. It is more effective to use the phase shift mask, the oblique incidence illumination method (particularly, the dipole illumination) in alignment with the longitudinal direction of line patterns as disclosed in Japanese Patent Application Laid-Open No. 6-188169, etc. properly in combination.

Where fine line-and-space (L/S) patterns (e.g., L/S of about 25-50 nm) are transcribed onto the substrate P by use of the projection optical system PL with the reduction rate of about 1/4 and the ArF excimer laser as exposure light, for example, as in the first to third examples, the mask M acts as a polarizer by the Wave guide effect, depending upon the structure of the mask M (e.g., minuteness of patterns and the thickness of chromium), and the diffracted light of the s-polarization component (TE polarization component) is more emitted from the mask than the diffracted light of the p-polarization component (TM polarization component) which degrades the contrast. In this case, it is also desirable to use the linearly polarized illumination as described above, but the randomly polarized light can also be used for illumination of the mask M to achieve the high resolution performance by use of the projection optical system having the large numerical

aperture NA of 0.9-1.3.

In cases where extremely fine line-and-space patterns on the mask M are transcribed onto the substrate P, the p-polarization component (TM polarization component) can be greater than the s-polarization component (TE polarization component) by virtue of the Wire Grid effect, but the high resolution performance can also be achieved even in the case of the large numerical aperture NA of the projection optical system such as 0.9-1.3, because the diffracted light of the s-polarization component (TE polarization component) is more emitted from the mask than the diffracted light of the p-polarization component (TM polarization component), for example, under the conditions that the ArF excimer laser is used as the exposure light, the projection exposure system has the reduction rate of about 1/4, and the line-and-space patterns greater than 25 nm are transcribed onto the substrate P.

Since the aforementioned fourth and fifth examples involve performing the exposure with the projection optical system having the projection magnification of not more than 1/8, they also have the advantage of reduced influence of the Wave guide effect and the Wire Grid effect due to the line-and-space patterns on the mask.

Furthermore, in addition to the linearly polarized illumination (s-polarized illumination) in alignment with the longitudinal direction of line patterns of the mask (reticle), it is also effective to adopt a combination of the polarized illumination using the linearly polarized light in the tangent (circumferential) direction of a circle with a center on the optical axis, with the obliquely incident illumination.

Particularly, in cases where the patterns of the mask (reticle) include line patterns extending in a predetermined direction and line patterns extending in a plurality of different directions mixed, the high imaging performance can also be achieved even in the case of the large numerical aperture NA of the projection optical system, by combinationally using the polarized illumination using the linearly polarized light in the tangent direction of a circle with a center on the optical axis, and the annular illumination.

Industrial Applicability

As described above, one aspect of the present invention involves filling the optical path between the projection optical system and the photosensitive substrate with the medium having the refractive index larger than 1.1, and repeating the exposure in each partial exposure region more than once in the projection exposure in one shot-area including a plurality of partial exposure regions. As a result, the present invention enables the high-resolution projection exposure with high throughput and, in turn, production of good microdevices, while securing the large effective image-side numerical aperture through the intervention of the high-refractive-index medium in the optical path between the projection optical system and the photosensitive substrate, using the dioptric projection optical system easy to manufacture and the mask of the ordinary size.

Another aspect of the present invention enables realization of the dioptric projection optical system capable of securing the relatively large effective imaging area, while securing the large effective image-side numerical aperture through the intervention of the high-refractive-

index medium in the optical path to the image surface. As a result, the exposure apparatus and exposure method using the projection optical system of the present invention are able to perform the high-resolution projection exposure with high throughput and, in turn, to produce good microdevices, while securing the large effective image-side numerical aperture through the intervention of the high-refractive-index medium in the optical path between the projection optical system and the photosensitive substrate, using the dioptric projection optical system easy to manufacture and the mask of the ordinary size, for example, by repeating the exposure in each partial exposure region more than once in the projection exposure in one shot-area including the plurality of partial exposure regions.

CLAIMS

1. An exposure method of effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate, the exposure method comprising:

a filling step of filling an optical path between the projection optical system and the photosensitive substrate with a medium having a refractive index larger than 1.1, where a refractive index of an atmosphere in an optical path of the projection optical system is 1; and

an exposure step of effecting a projection exposure in one shot-area on the photosensitive substrate,

wherein the one shot-area includes a plurality of partial exposure regions, and

wherein the exposure step is to repeat an exposure in the partial exposure region more than once.

2. The exposure method according to Claim 1,

wherein the exposure step comprises: a still exposure step of performing a still projection exposure in the partial exposure region in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system; and

a moving step of moving at least the photosensitive substrate relative to the projection optical system, in order to perform a still projection exposure in another partial exposure region different from the partial exposure region already subjected to the still projection exposure.

3. The exposure method according to Claim 2,

wherein the projection optical system has a projection

magnification of not more than approximately $1/5$, and

5 wherein the exposure step is to repeat at least twice a still projection exposure in the partial exposure region having a size of approximately a half of the one shot-area, thereby effecting the projection exposure in the one shot-area.

4. The exposure method according to Claim 3,

10 wherein the exposure step is to repeat only twice the still projection exposure in the partial exposure region having the size of approximately a half of the one shot-area, thereby effecting the projection exposure in the one shot-area.

5. The exposure method according to Claim 3 or 4, further comprising:

15 a replacing step of replacing the mask with another between the first still projection exposure and the second still projection exposure in the exposure step.

6. The exposure method according to Claim 2,

wherein the projection optical system has a projection magnification of approximately $1/4$, and

20 wherein the exposure step is to repeat at least four times a still projection exposure in the partial exposure region having a size of approximately a quarter of the one shot-area, thereby effecting the projection exposure in the one shot-area.

7. The exposure method according to Claim 6,

25 wherein the exposure step is to repeat only four times a still projection exposure in the partial exposure region having the size of approximately a quarter of the one shot-area, thereby effecting the

projection exposure in the one shot-area.

8. The exposure method according to Claim 1 or 2,
wherein the projection optical system has a magnification of not
more than 1/8.

5 9. The exposure method according to Claim 8,
wherein the exposure step is to perform projection exposures in
a plurality of shot-areas and to repeat exposures in partial exposure
regions not adjoining each other, more than once.

10 10. The exposure method according to Claim 9,
wherein the exposure step is first to perform exposures in
specific partial exposure regions among respective partial exposure
regions of the plurality of shot-areas and thereafter to perform exposures
in other partial exposure regions among the respective partial exposure
regions of the plurality of shot-areas.

15 11. The exposure method according to Claim 10, further
comprising:

a replacing step of replacing the mask with another between the
exposures in the specific partial exposure regions and the exposures in
the other partial exposure regions in the exposure step.

20 12. The exposure method according to any one of Claims 8 to
11,

wherein the partial exposure step is to perform a projection
exposure in a partial exposure region having a size of approximately a
quarter of the one shot-area, and

25 wherein the exposure step comprises at least four the partial
exposure steps.

13. The exposure method according to any one of Claims 1 to 11,

wherein at least two partial exposure regions among the plurality of partial exposure regions overlap in part with each other.

5 14. An exposure method of effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate, the exposure method comprising:

10 a filling step of filling an optical path between the projection optical system and the photosensitive substrate with a medium having a refractive index larger than 1.1, where a refractive index of an atmosphere in an optical path of the projection optical system is 1;

15 a first exposure step of performing a projection exposure in a first still exposure region on the photosensitive substrate in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system;

20 a moving step of moving at least the photosensitive substrate relative to the projection optical system, in order to perform a projection exposure in a second still exposure region not adjoining the first still exposure region subjected to the projection exposure in the first exposure step, the moving step being executed directly after the first exposure step; and

25 a second exposure step of performing the projection exposure in the second still exposure region on the photosensitive substrate in the state in which the mask and the photosensitive substrate are kept still relative to the projection optical system, the second exposure step being

executed directly after the moving step.

15. The exposure method according to Claim 14,
wherein the mask is not replaced between the first exposure step
and the second exposure step.

5 16. The exposure method according to Claim 14 or 15, further
comprising:

a third exposure step of performing a projection exposure in a
third still exposure region different from the first and second still
exposure regions, in the state in which the mask and the photosensitive
10 substrate are kept still relative to the projection optical system,

wherein the third still exposure region is located between the
first still exposure region and the second still exposure region.

17. The exposure method according to Claim 16, further
comprising:

15 a replacing step of replacing the mask with another between the
second exposure step and the third exposure step.

18. The exposure method according to Claim 16 or 17,
wherein the third still exposure region overlaps in part with the
first still exposure region or with the second still exposure region.

20 19. The exposure method according to any one of Claims 1 to
18,

wherein the projection optical system is a dioptric system
comprised of only a plurality of light transmitting members.

25 20. The exposure method according to any one of Claims 1 to
19,
wherein the medium contains water.

21. An exposure apparatus for effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate,

5 wherein an optical path between the projection optical system and the photosensitive substrate is filled with a medium having a refractive index larger than 1.1 where a refractive index of an atmosphere in an optical path of the projection optical system is 1,

10 wherein the projection optical system has a still exposure region substantially smaller than one shot-area to be formed on the photosensitive substrate, and

wherein the projection optical system repeats a projection exposure in a portion of the shot-area more than once in the projection exposure in the shot-area.

22. The exposure apparatus according to Claim 21,

15 wherein a still projection exposure in a portion of the shot-area is performed in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system, and wherein at least the photosensitive substrate is moved relative to the projection optical system, in order to perform a still projection exposure
20 in a portion different from the portion of the shot-area.

23. The exposure apparatus according to Claim 22,

wherein the still exposure region has a size of approximately a half of the shot-area and wherein the projection optical system has a projection magnification of not more than approximately 1/5.

25 24. The exposure apparatus according to Claim 22,

wherein the still exposure region has a size of approximately a

quarter of the shot-area and wherein the projection optical system has a projection magnification of approximately $1/4$.

25. The exposure apparatus according to Claim 22,
wherein the still exposure region has a size of approximately a
5 quarter of the shot-area and wherein the projection optical system has a
projection magnification of not more than $1/8$.

26. The exposure apparatus according to any one of Claims 21
to 25,
wherein the portion and the different portion of the shot-area
10 overlap in part with each other.

27. The exposure apparatus according to any one of Claims 21
to 26,
wherein the projection optical system is a dioptric system
comprised of only a plurality of light transmitting members.

15 28. The exposure apparatus according to any one of Claims 21
to 27,
wherein the medium contains water.

29. An exposure apparatus for effecting a projection exposure
of a reduced image of a pattern formed on a mask, through a projection
20 optical system onto a photosensitive substrate, the exposure apparatus
comprising:

a substrate stage for holding the photosensitive substrate in a
movable state;

25 means for filling an optical path between the projection optical
system and the photosensitive substrate with a medium having a
refractive index larger than 1.1, where a refractive index of an

atmosphere in an optical path of the projection optical system is 1; and

control means for controlling at least the substrate stage so as to perform a projection exposure in a first still exposure region on the photosensitive substrate in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system, to, subsequent to the projection exposure in the first still exposure region, move at least the photosensitive substrate relative to the projection optical system in order to perform a projection exposure in a second still exposure region not adjoining the first still exposure region subjected to the projection exposure in the first exposure step, and to, subsequent to the relative movement of the photosensitive substrate, perform the projection exposure in the second still exposure region on the photosensitive substrate in the state in which the mask and the photosensitive substrate are kept still relative to the projection optical system.

30. The exposure apparatus according to Claim 29,

wherein the mask is not replaced between the projection exposure in the first still exposure region and the projection exposure in the second still exposure region.

31. The exposure apparatus according to Claim 29 or 30

wherein a projection exposure in a third still exposure region different from the first and second still exposure regions is performed in the state in which the mask and the photosensitive substrate are kept still relative to the projection optical system, and

wherein the third still exposure region is located between the first still exposure region and the second still exposure region.

32. The exposure apparatus according to Claim 31,
wherein the mask is replaced with another between the second
exposure step and the third exposure step.

5 33. The exposure apparatus according to Claim 31 or 32,
wherein the third still exposure region adjoins the first still
exposure region or the second still exposure region.

34. The exposure apparatus according to Claim 31 or 32,
wherein the third still exposure region overlaps in part with the
first still exposure region or with the second still exposure region.

10 35. The exposure apparatus according to any one of Claims 29
to 34,

wherein the medium contains water.

36. A projection optical system for forming a reduced image of
a first surface on a second surface,

15 wherein an optical path between the projection optical system
and the second surface is filled with a medium having a refractive index
larger than 1.1 where a refractive index of an atmosphere in an optical
path of the projection optical system is 1,

20 wherein every optical member having a power in the projection
optical system is a transmitting optical member,

wherein a magnification of the projection optical system is not
more than $1/8$, and

wherein the projection optical system is substantially telecentric
on both the first surface side and the second surface side.

25 37. The projection optical system according to Claim 36,
satisfying the following condition:

$$0.18 < L2/LA < 0.245 \quad (1),$$

where L2 is a distance from a pupil position on the second surface side to the second surface and LA a distance from the first surface to the second surface.

5 38. The projection optical system according to Claim 36 or 37, comprising:

at least one variable aperture stop disposed at or near a pupil position on the second surface side.

10 39. The projection optical system according to any one of Claims 36 to 38, comprising the following lens units arranged in order from the first surface side:

15 a first lens unit having a positive refracting power; a second lens unit having a negative refracting power; a third lens unit having a positive refracting power; a fourth lens unit having a negative refracting power; a fifth lens unit having a positive refracting power; an aperture stop; and a sixth lens unit having a positive refracting power;

20 wherein, where a size of a region occupied on each optical surface by a beam from a point on an optical axis of the first surface is defined as a partial diameter, the projection optical system satisfies the following condition:

$$0.04 < P2/PX < 0.2 \quad (2),$$

where PX is a maximum partial diameter in the projection optical system and P2 a minimum partial diameter in the second lens unit.

25 40. The projection optical system according to Claim 39, satisfying the following condition:

$$0.4 < D4/D0 < 0.9 \quad (3),$$

where D4 is a minimum clear aperture radius of a lens in the fourth lens unit and D0 a clear aperture radius of the first surface.

41. The projection optical system according to any one of Claims 36 to 38, comprising the following lens units arranged in order from the first surface side:

a first lens unit having a negative refracting power; a second lens unit having a positive refracting power; a third lens unit having a negative refracting power; a fourth lens unit having a positive refracting power; an aperture stop; and a fifth lens unit having a positive refracting power;

wherein, where a size of a region occupied on each optical surface by a beam from a point on an optical axis of the first surface is defined as a partial diameter, the projection optical system satisfies the following condition:

$$0.07 < P3/PX < 0.23 \quad (4),$$

where PX is a maximum partial diameter in the projection optical system and P3 a minimum partial diameter in the third lens unit.

42. The projection optical system according to Claim 41, satisfying the following condition:

$$0.35 < D3/D0 < 0.85 \quad (5),$$

where D3 is a minimum clear aperture radius of a lens in the third lens unit and D0 a clear aperture radius of the first surface.

43. The projection optical system according to any one of Claims 36 to 42,

wherein the medium contains water.

44. An exposure apparatus comprising: an illumination system for illuminating a mask set as the first surface; and the projection optical system as set forth in any one of Claims 36 to 43, for forming an image of a pattern formed on the mask, on a photosensitive substrate set as the second surface.

45. The exposure apparatus according to Claim 44, wherein the image of the pattern is formed in a portion on the photosensitive substrate in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system, and wherein at least the photosensitive substrate is moved relative to the projection optical system, in order to form the image of the pattern in another portion different from the portion, in the state in which the mask and the photosensitive substrate are kept still relative to the projection optical system.

46. The exposure apparatus according to Claim 45, wherein the portion and the different portion of the shot-area overlap in part with each other.

47. An exposure method comprising:
an illumination step of illuminating a mask set as the first surface; and

an exposure step of effecting a projection exposure of an image of a pattern formed on the mask, onto a photosensitive substrate set as the second surface, through the projection optical system as set forth in any one of Claims 36 to 43.

48. The exposure method according to Claim 47, wherein the exposure step is to perform a projection exposure in

one shot-area including a plurality of partial exposure regions, and

wherein the exposure step comprises a plurality of partial exposure steps each of which is to perform a projection exposure in the partial exposure region.

5 49. The exposure method according to Claim 48,

wherein the partial exposure step is to perform a projection exposure in a partial exposure region having a size of approximately a quarter of the one shot-area, and

10 wherein the exposure step comprises at least four the partial exposure steps.

50. The exposure method according to Claim 48 or 49,

15 wherein the partial exposure step is to perform a still projection exposure in the partial exposure region in a state in which the mask and the photosensitive substrate are kept still relative to the projection optical system.

51. The exposure method according to any one of Claims 48 to 50, further comprising:

20 a mask replacing step of replacing the mask with another between the first partial exposure step and the second partial exposure step in the exposure step.

52. The exposure method according to Claim 51,

wherein the exposure step is to perform projection exposures in a plurality of shot-areas, and

25 wherein the mask replacing step is executed between the first partial exposure step for the plurality of shot-areas and the second partial exposure step for the plurality of shot-areas.

53. An exposure method of effecting a projection exposure of a reduced image of a pattern formed on a mask, through a projection optical system onto a photosensitive substrate, the exposure method comprising:

5 a preparation step of preparing the projection optical system having a magnification of not more than $1/8$;

 a filling step of filling an optical path between the projection optical system and the photosensitive substrate with a medium having a refractive index larger than 1.1, where a refractive index of an atmosphere in an optical path of the projection optical system is 1; and

10 an exposure step of effecting a projection exposure in one shot-area on the photosensitive substrate,

 wherein the exposure step is to perform the projection exposure in one shot-area including a plurality of partial exposure regions, and

15 wherein the exposure step comprises a plurality of partial exposure steps each of which is to perform a projection exposure in the partial exposure region.

54. The exposure method according to Claim 53,

20 wherein the partial exposure step is to perform a projection exposure in a partial exposure region having a size of approximately a quarter of the one shot-area, and

 wherein the exposure step comprises at least four the partial exposure steps.

55. The exposure method according to Claim 53 or 54,

25 wherein the partial exposure step is to perform a still projection exposure in the partial exposure region in a state in which the mask and

the photosensitive substrate are kept still relative to the projection optical system.

56. The exposure method according to any one of Claims 53 to 55, further comprising:

5 a mask replacing step of replacing the mask with another between the first partial exposure step and the second partial exposure step in the exposure step.

57. The exposure method according to Claim 56,

10 wherein the exposure step is to perform projection exposures in a plurality of shot-areas, and

 wherein the mask replacing step is executed between the first partial exposure step for the plurality of shot-areas and the second partial exposure step for the plurality of shot-areas.